

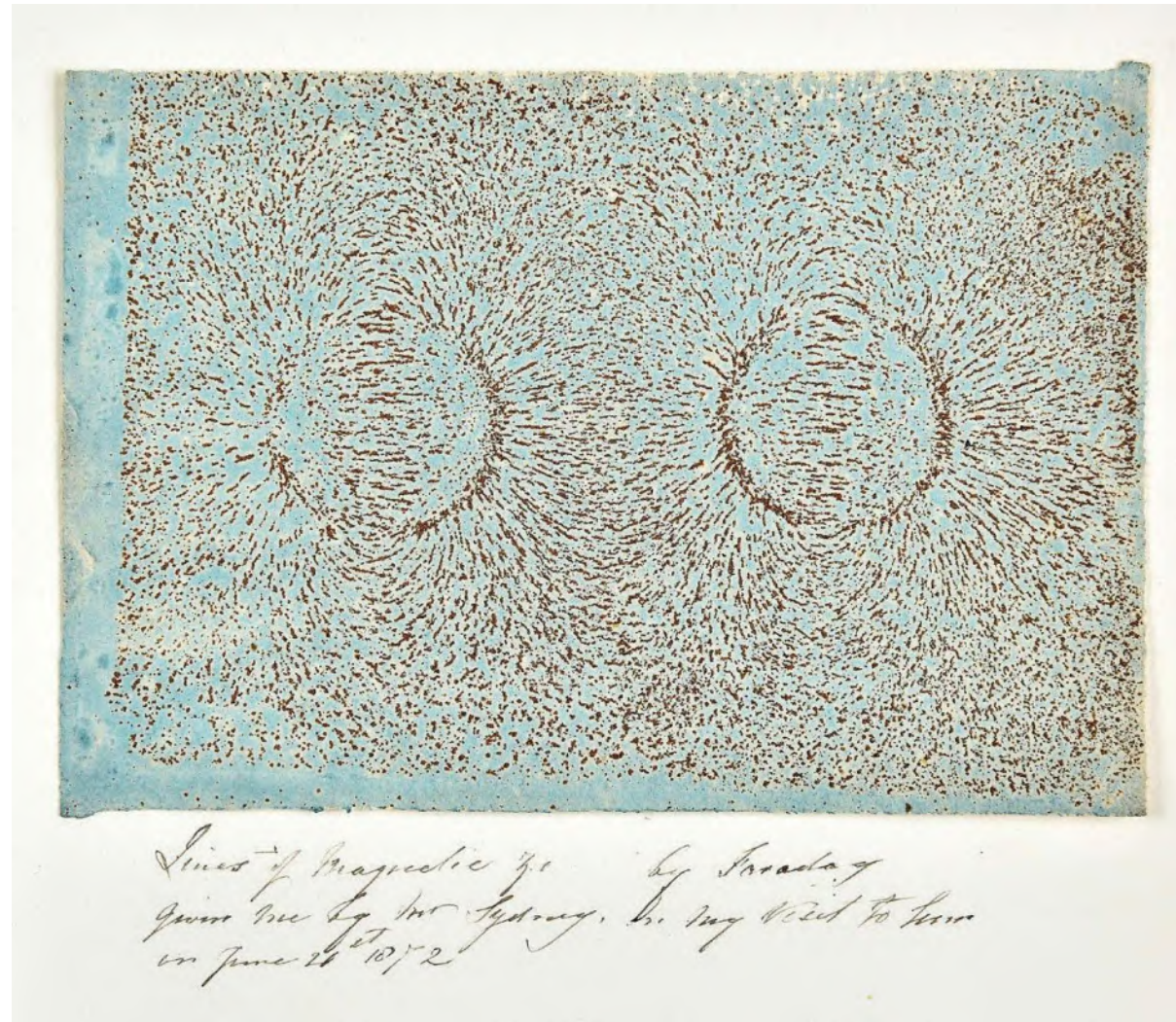
# Unraveling Microscopic Mechanisms in Condensed Matter Systems with Local Magnetic Field Probes

Prof. Martino Poggio  
Dr. Jelena Trbovic

11 February 2021



# Faraday's iron filings



M. Faraday, ca. 1830s

# Scanning tunnelling spectroscopy on atomic-scale

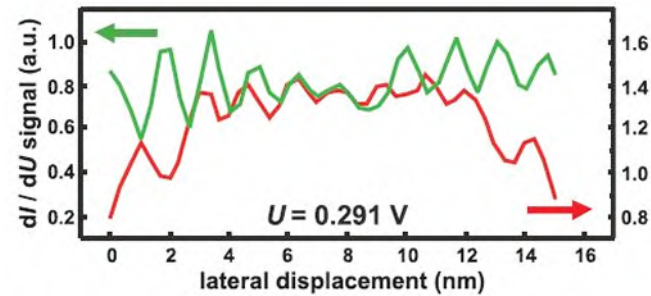
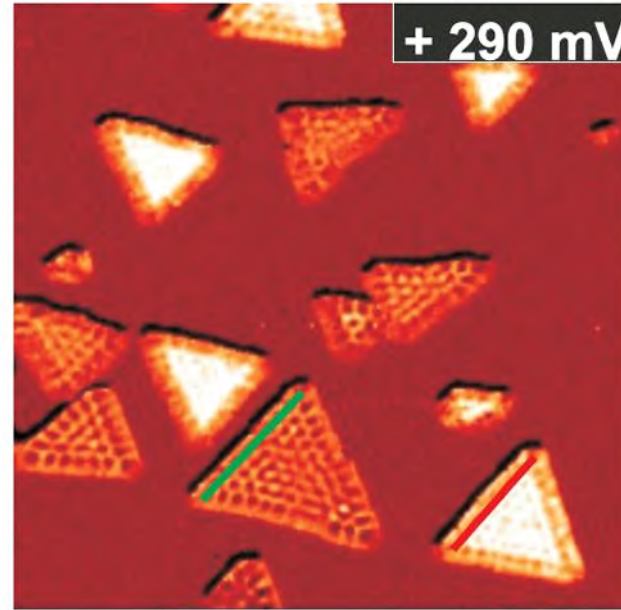
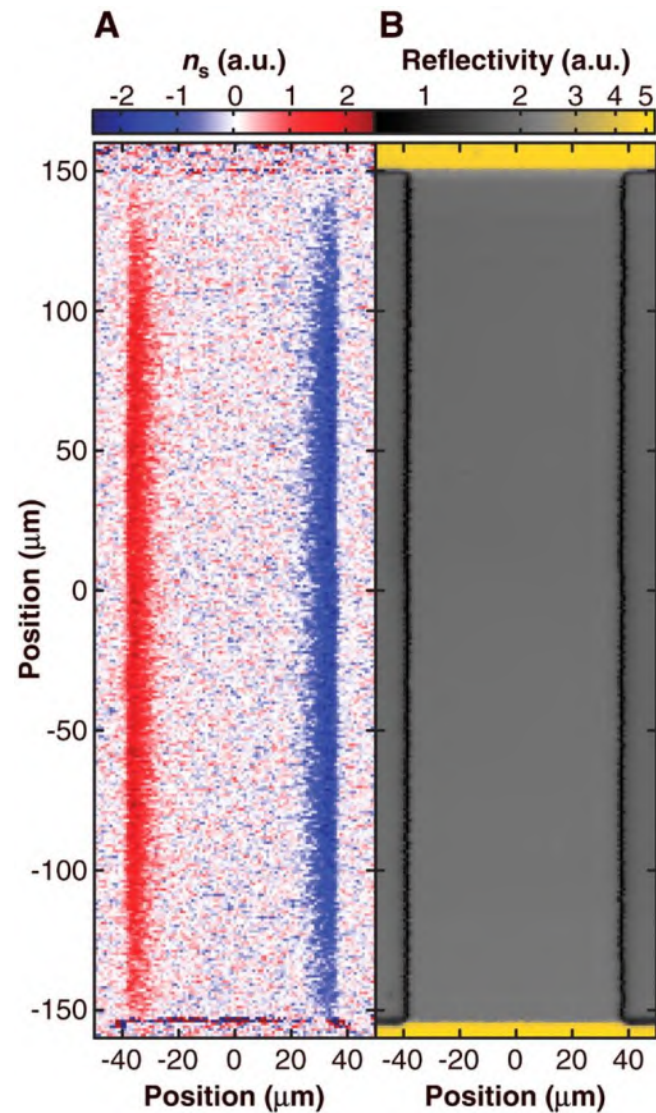
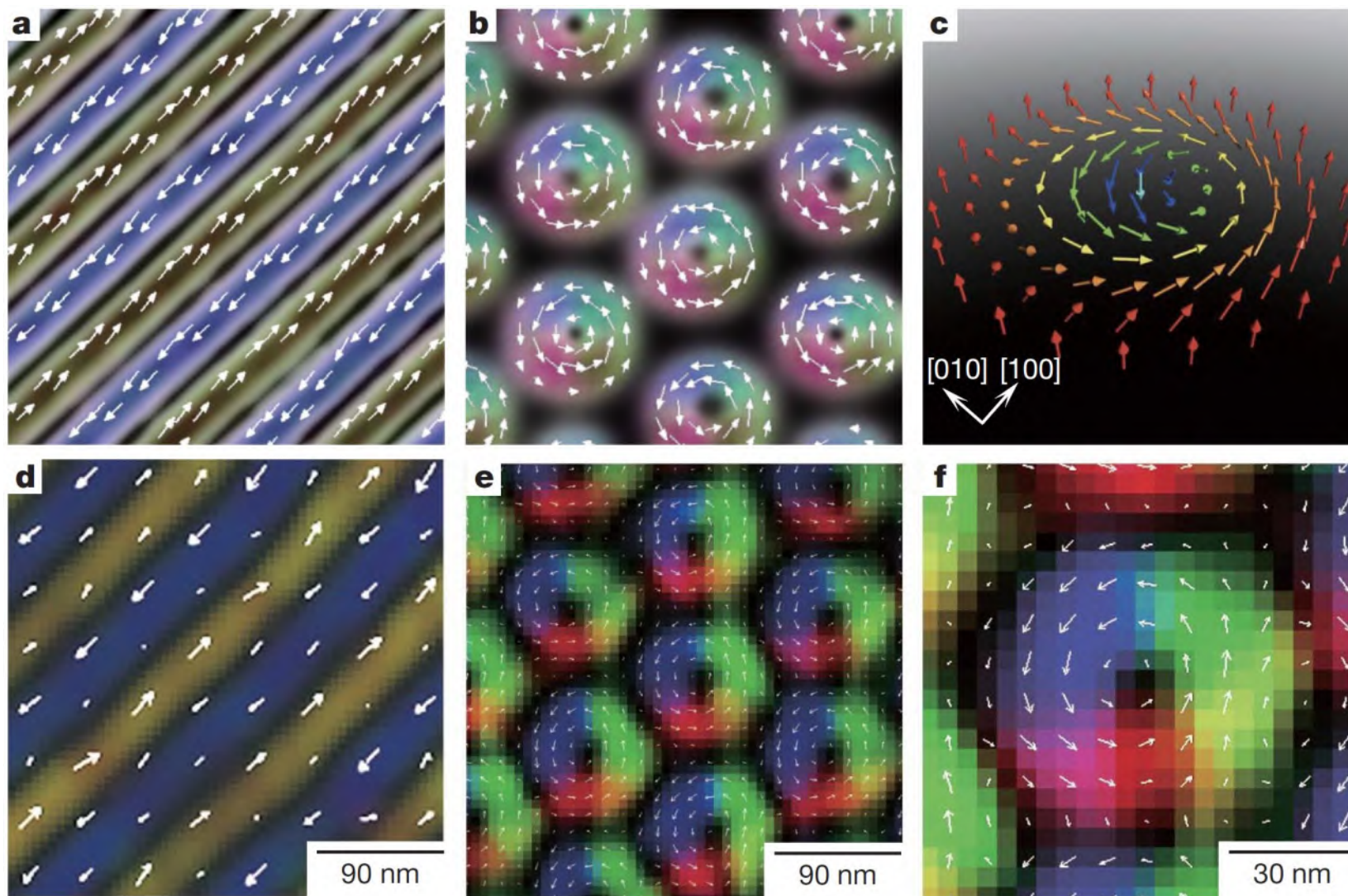


FIG. 44. (Color) SP-STS data ( $60 \times 60 \text{ nm}^2$ ) revealing the spin dependence of the 2D electronic confinement states in nanoscale Co islands which manifests itself by a spin-dependent oscillation amplitude of the confinement states for differently magnetized Co nanoislands. From Pietzsch *et al.*, 2006.

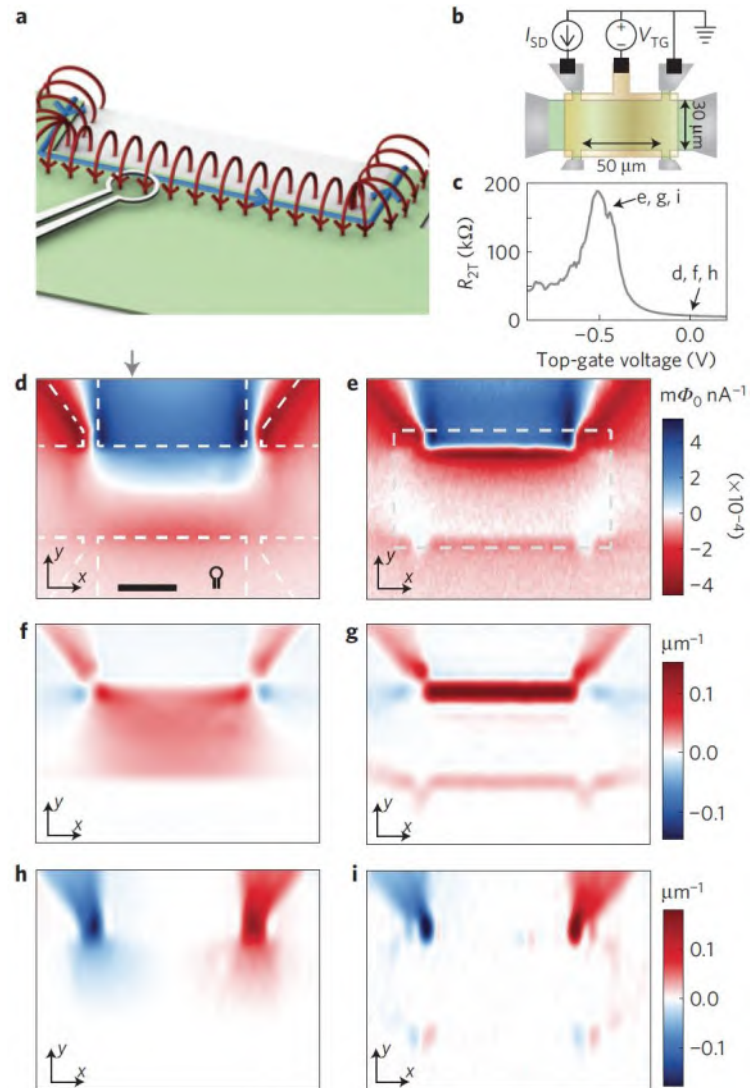
# Magneto-optical imaging of local spin-polarization



# Lorentz microscopy of skyrmion crystals



# SQUID microscopy of edge currents



# Emergence of 2D materials and vdW heterostructures

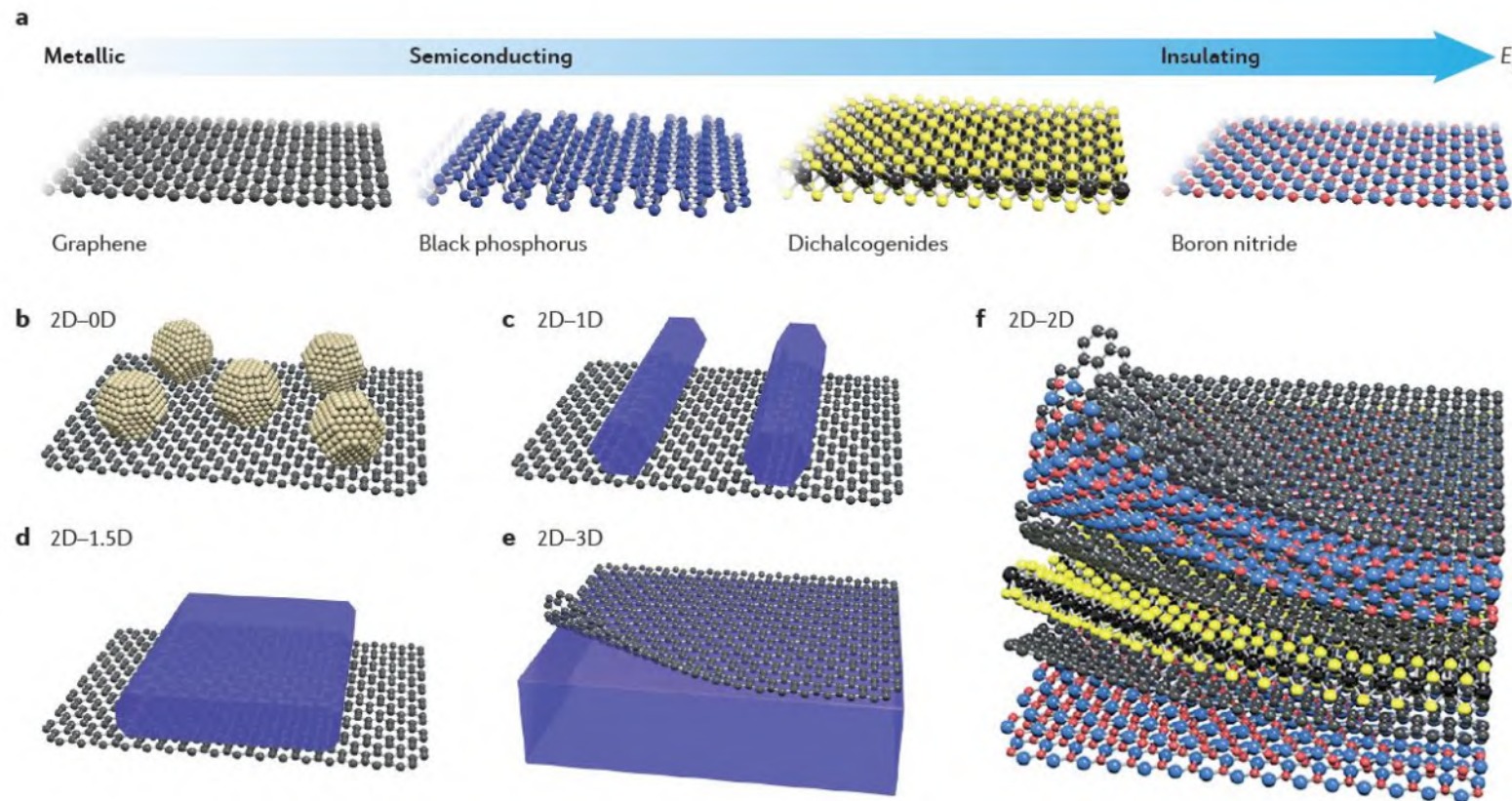


Figure 1 | **Two-dimensional layered materials and van der Waals heterostructures.** **a** | A broad library of two-dimensional layered materials (2DLMs) with varying chemical composition, atomic structures and electronic properties, with an increasing bandgap from left to right. **b-f** | Van der Waals heterostructures formed by integrating the dangling-bond-free 2DLMs with 0D nanoparticles or quantum dots (panel **b**), 1D nanowires (panel **c**), 1.5D nanoribbons (panel **d**), 3D bulk materials (panel **e**) and 2D nanosheets (panel **f**).

# Emergence of 2D materials and vdW heterostructures

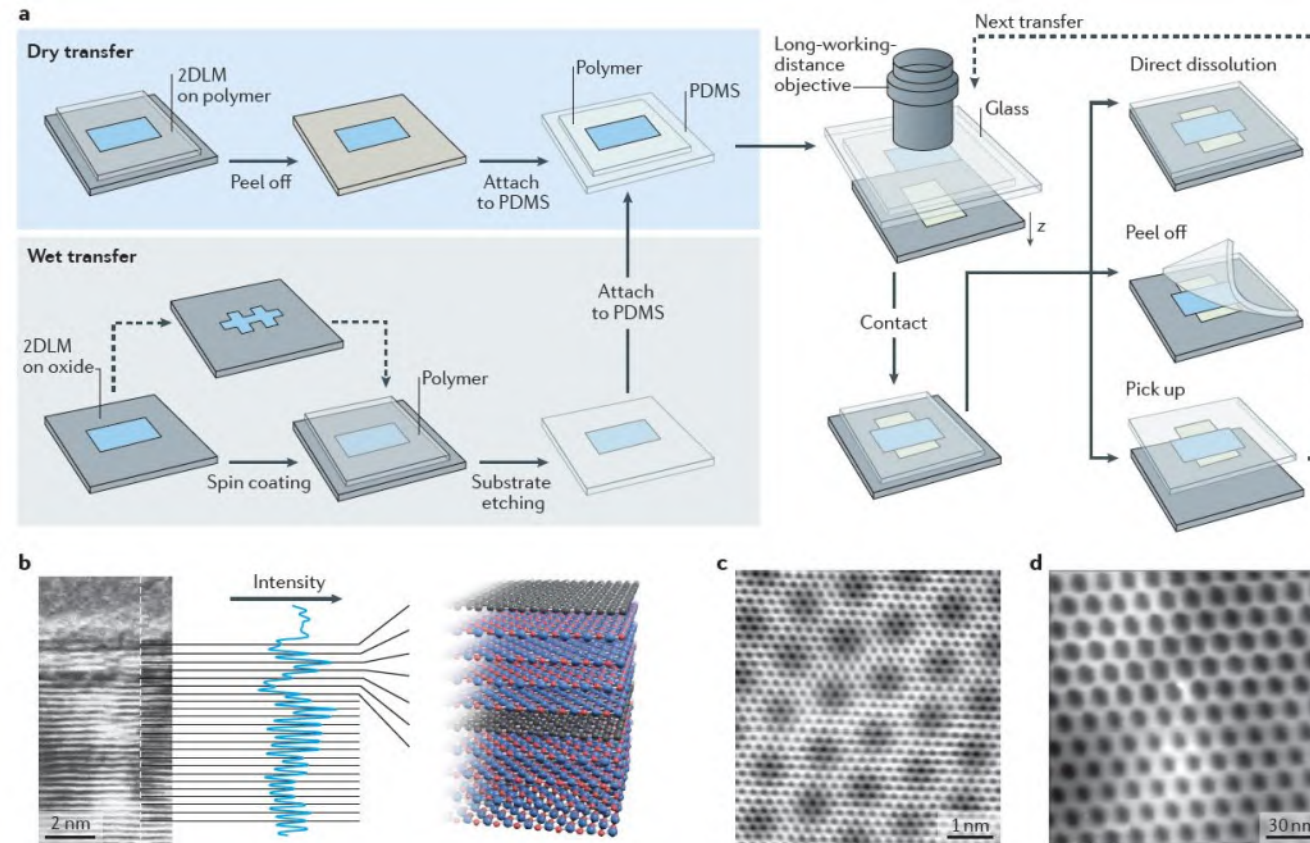


Figure 2 | **Assembly and characterization of 2D-2D vdWHs.** **a** | Schematic illustration of state-of-the-art alignment transfer processes for van der Waals heterostructure (vdWH) integration. Wet and dry transfer techniques are used to attach the target sheet to the stamp material. The stamp is then attached to a glass slide and placed in a transfer microscope. Micromanipulators allow for the precise alignment of sheets using a long-working-distance objective lens. The polymer transfer stamp can either be chemically dissolved away, mechanically peeled off or used to pick up the entire stack for further transfer steps. **b** | False-coloured high-resolution cross-sectional scanning tunnelling electron microscopy image of the BN-graphene-BN-graphene stack (left) and a corresponding schematic representation (right). **c,d** | Moiré pattern of graphene on BN (panel **c**) and a much larger moiré pattern of the commensurate-incommensurate transition of graphene on BN (panel **d**). 2DLM, two-dimensional layered material; BN, boron nitride; PDMS, poly(dimethyl siloxane). Panel **b** is from REF. 71, Nature Publishing Group. Panel **c** is courtesy of Brian LeRoy, University of Arizona, USA. Panel **d** is from REF. 73, Nature Publishing Group.

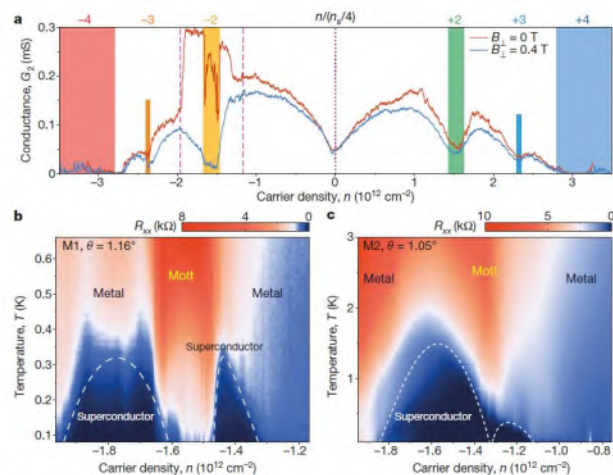
# Correlated states in atomically layered materials

## ARTICLE

doi:10.1038/nature26160

### Unconventional superconductivity in magic-angle graphene superlattices

Yuan Cao<sup>1</sup>, Valla Fatemi<sup>1</sup>, Shiang Fang<sup>2</sup>, Kenji Watanabe<sup>3</sup>, Takashi Taniguchi<sup>3</sup>, Efthimos Kaxiras<sup>2,4</sup> & Pablo Jarillo-Herrero<sup>1</sup>



**Figure 2 | Gate-tunable superconductivity in magic-angle TBG.** a, Two-probe conductance  $G_2 = I/V_{\text{bias}}$  of device M1 ( $\theta = 1.16^\circ$ ) measured in zero magnetic field (red) and at a perpendicular field of  $B_{\perp} = 0.4 \text{ T}$  (blue). The curves exhibit the typical V-shaped conductance near charge neutrality ( $n = 0$ , vertical purple dotted line) and insulating states at the superlattice bandgaps  $n = \pm n_c$ , which correspond to filling  $\pm 4$  electrons in each moiré unit cell (blue and red bars). They also exhibit reduced conductance at intermediate integer fillings of the superlattice owing to Coulomb interactions (other coloured bars). Near a filling of  $-2$  electrons per unit cell, there is considerable conductance enhancement at zero field that is suppressed in  $B_{\perp} = 0.4 \text{ T}$ . This enhancement signals the onset of

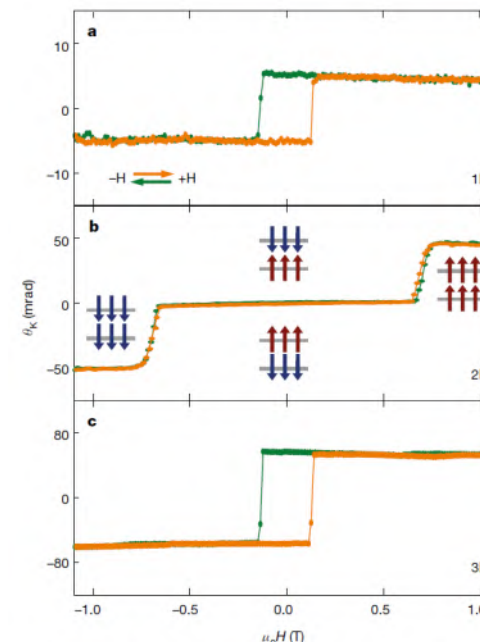
superconductivity. Measurements were conducted at  $70 \text{ mK}$ ;  $V_{\text{bias}} = 10 \mu\text{V}$ . b, Four-probe resistance  $R_{xy}$ , measured at densities corresponding to the region bounded by pink dashed lines in a, versus temperature. Two superconducting domes are observed next to the half-filling state, which is labelled 'Mott' and centred around  $-n_c/2 = -1.58 \times 10^{12} \text{ cm}^{-2}$ . The remaining regions in the diagram are labelled 'metal' owing to the metallic temperature dependence. The highest critical temperature observed in device M1 is  $T_c = 0.5 \text{ K}$  (at 50% of the normal-state resistance). c, As in b, but for device M2, showing two asymmetric and overlapping domes. The highest critical temperature in this device is  $T_c = 1.7 \text{ K}$ .

## LETTER

doi:10.1038/nature22391

### Layer-dependent ferromagnetism in a van der Waals crystal down to the monolayer limit

Bevin Huang<sup>1\*</sup>, Genevieve Clark<sup>2\*</sup>, Efrén Navarro-Moratalla<sup>3\*</sup>, Dahlia R. Klein<sup>3</sup>, Ran Cheng<sup>4</sup>, Kyle L. Seyler<sup>1</sup>, Ding Zhong<sup>1</sup>, Emma Schmidgall<sup>1</sup>, Michael A. McGuire<sup>5</sup>, David H. Cobden<sup>1</sup>, Wang Yao<sup>6</sup>, Di Xiao<sup>4</sup>, Pablo Jarillo-Herrero<sup>3</sup> & Xiaodong Xu<sup>1,2</sup>



**Figure 3 | Layer-dependent magnetic ordering in atomically-thin CrI<sub>3</sub>.** a, MOKE signal on a monolayer (1L) CrI<sub>3</sub> flake, showing hysteresis in the Kerr rotation as a function of applied magnetic field, indicative of ferromagnetic behaviour. b, MOKE signal from a bilayer CrI<sub>3</sub> showing vanishing Kerr rotation for applied fields  $\pm 0.65 \text{ T}$ , suggesting antiferromagnetic behaviour. Insets depict bilayer (2L) magnetic ground states for different applied fields. c, MOKE signal on a trilayer (3L) flake, showing a return to ferromagnetic behaviour.

# How to decipher the mechanism behind these phenomena?

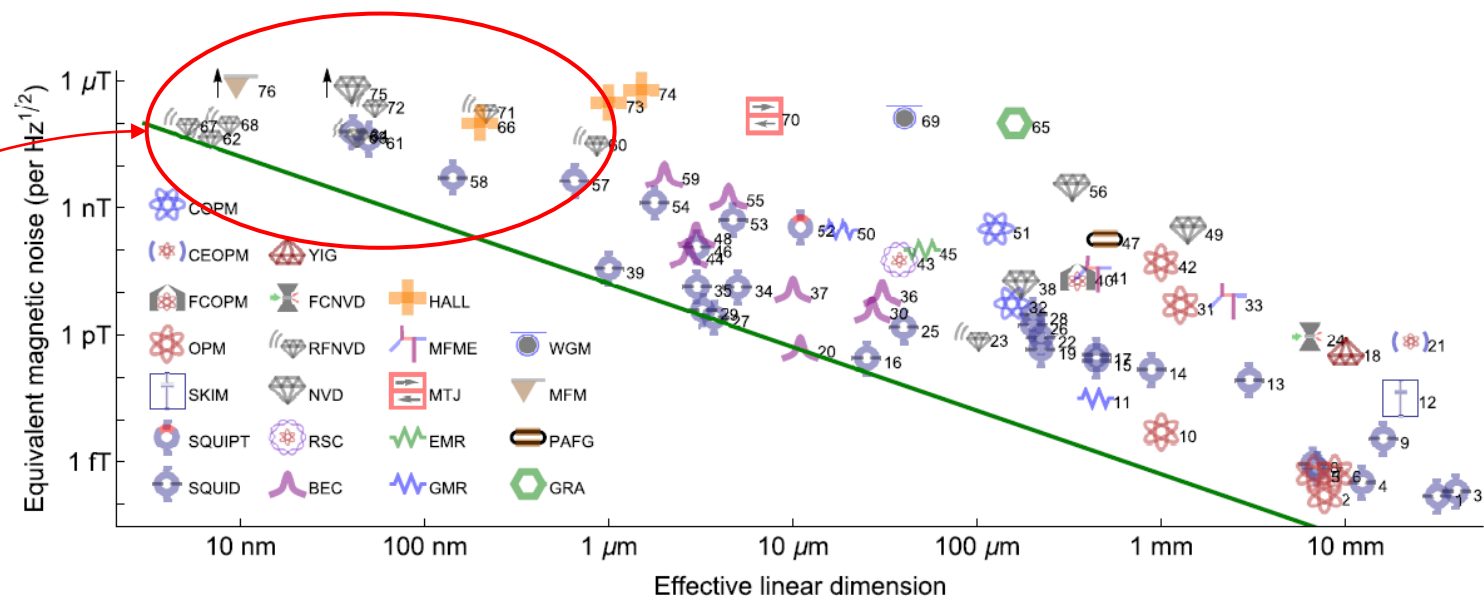


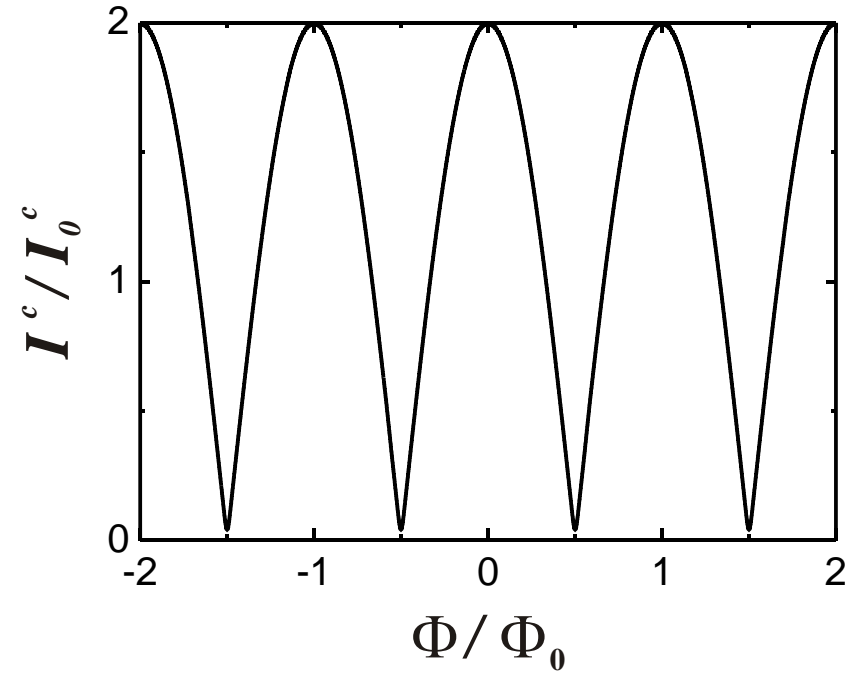
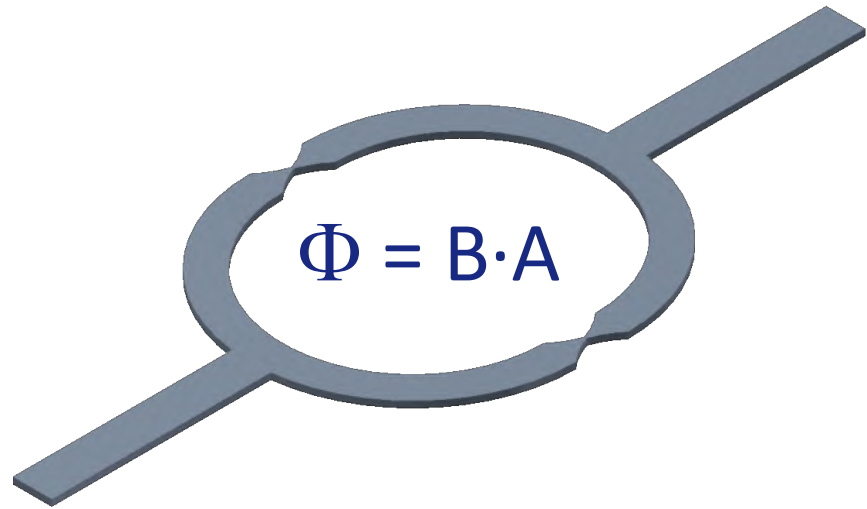
FIG. 2. Reported magnetic sensitivity  $\delta B\sqrt{T}$  for different sensor technologies versus size of the sensitive region. Effective linear dimension  $l_{\text{eff}}$  indicates  $\sqrt{\text{area}}$  for planar sensors and  $\sqrt[3]{\text{volume}}$  for volumetric ones. For pointlike systems such as single spins,  $l_{\text{eff}}$  indicates  $\sqrt[3]{\text{volume}}$  for a sphere with radius equal to the minimum source-detector distance. For work reporting sensitivity in units of magnetic dipole moment, we convert to field units using the reported sample distance. Excepting RFNVD, noise levels are the lowest reported value at frequency  $\leq 1$  kHz. An arrow indicates that the value is off the scale. SQUID, superconducting quantum interference device; SQUIPT, superconducting quantum interference proximity transistor; SKIM, superconducting kinetic impedance magnetometer; OPM, optically pumped magnetometer; FCOPM, OPM with flux concentrators; CEOPM, cavity-enhanced OPM; COPM, OPM with cold thermal atoms; BEC, Bose-Einstein condensate; RSC, Rydberg Schrödinger cat; NVD, nitrogen-vacancy center in diamond; RFNVD, radio-frequency NVD; FCNVD, NVD with flux concentrators; YIG, yttrium-aluminum-garnet; GMR, giant magnetoresistance; EMR, extraordinary magnetoresistance; MTJ, magnetic tunnel junction; MEMF, magnetoelectric multiferroic; HALL, Hall-effect sensor; GRA, graphene; PAFG, parallel gating fluxgate; MFM, magnetic force microscope; WGM, whispering-gallery mode magnetostrictive. Line shows  $E_R \equiv \langle \delta B^2 \rangle T_{\text{eff}}^3 / (2\mu_0) = \hbar$ . Numeric labels refer to Table I.

Map weak magnetic field patterns with high spatial resolution

# Outline

- Scanning SQUID microscopy
  - SQUID-on-tip sensors
  - Magnetic imaging with SQUID-on-tip
- Zurich Instruments lock-in amplifiers
  - Measurement principles
  - Multiple mode measurement and control
- Magnetic force microscopy
  - Scaling down the sensor
  - NW MFM
- Comparison between techniques
  - Which sensor for which application?
  - Prospects for improvement

# Superconducting quantum interference device (SQUID)



SQUID critical current:  $I^c(\Phi) = 2I_0^c \cos|\pi\Phi / \Phi_0|$

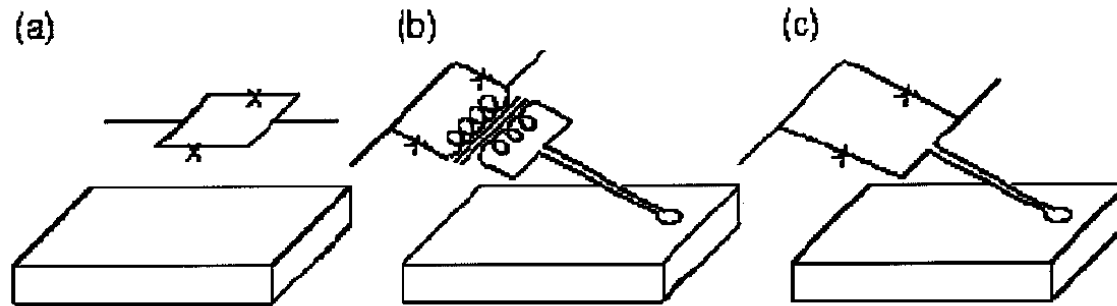
# SCANNING SQUID MICROSCOPY

*John R. Kirtley*

IBM T. J. Watson Research Center, Yorktown Heights, New York 10598;  
e-mail: kirtley@watson.ibm.com

*John P. Wikswo, Jr.*

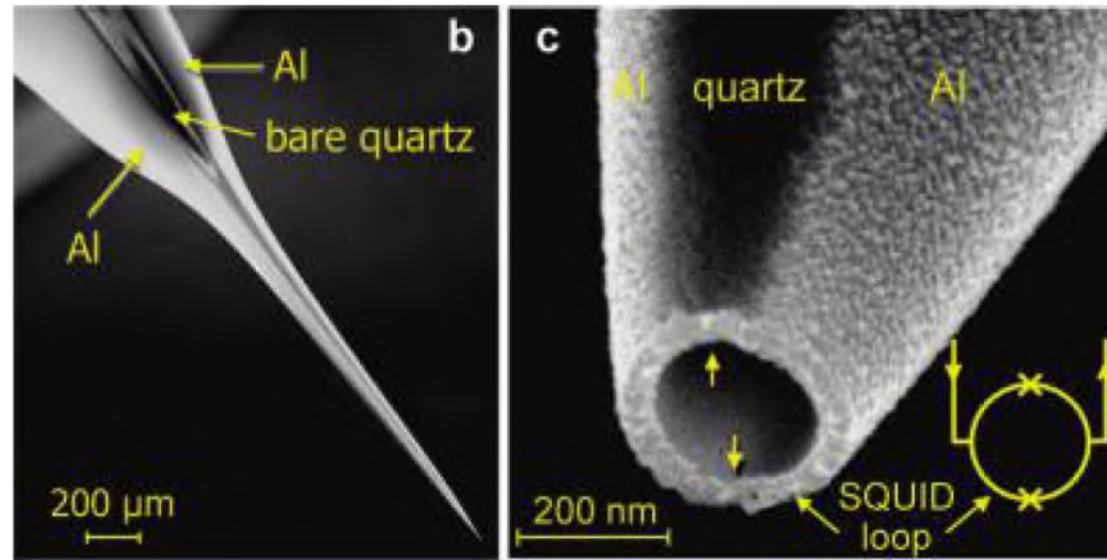
Department of Physics and Astronomy, Vanderbilt University, Nashville,  
Tennessee 37235; e-mail: wikswojp@ctrvax.vanderbilt.edu



# Self-Aligned Nanoscale SQUID on a Tip

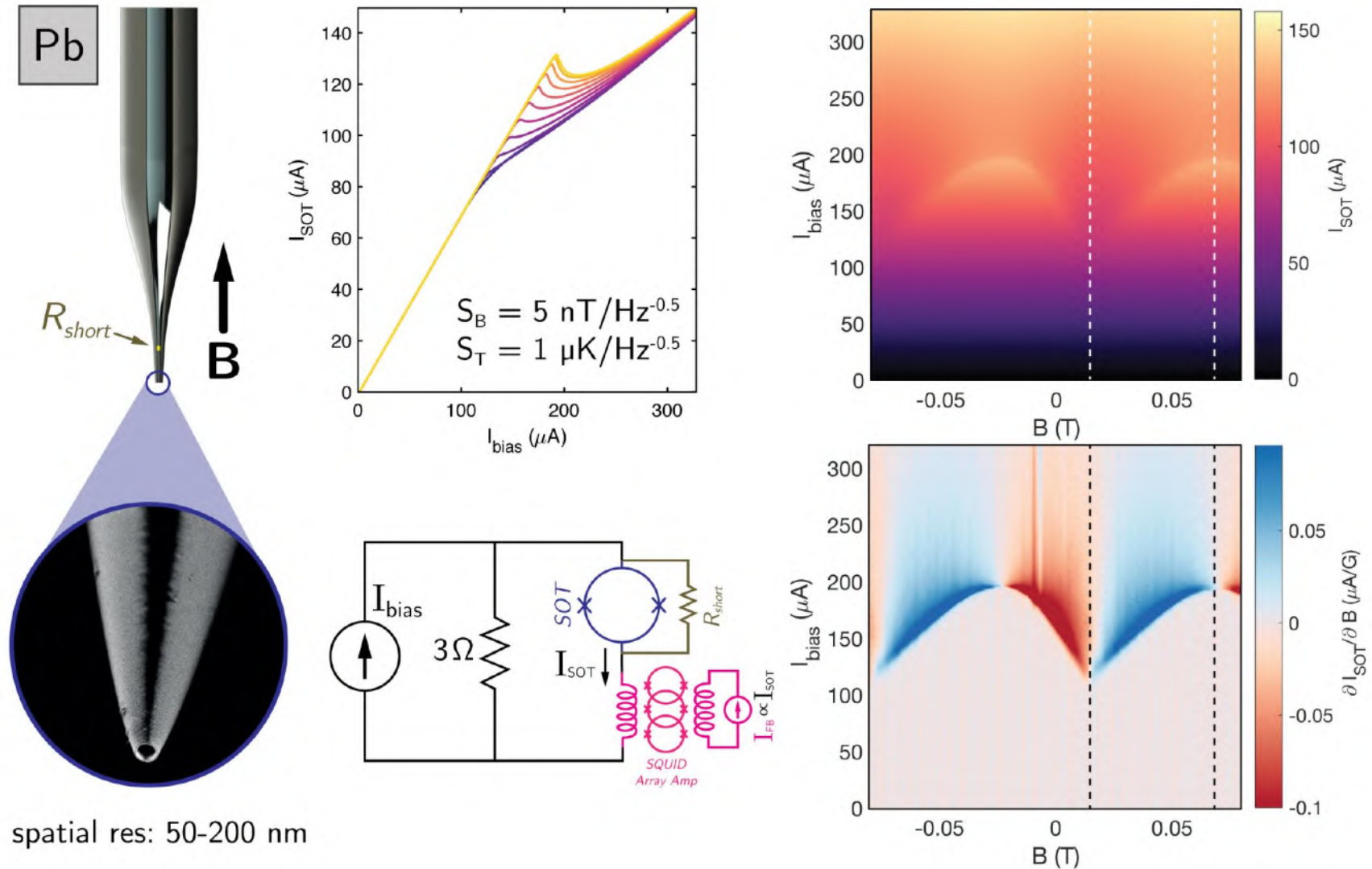
Amit Finkler,<sup>\*,†</sup> Yehonathan Segev,<sup>†</sup> Yuri Myasoedov,<sup>†</sup> Michael L. Rappaport,<sup>†</sup>  
Lior Ne'eman,<sup>†</sup> Denis Vasyukov,<sup>†</sup> Eli Zeldov,<sup>†</sup> Martin E. Huber,<sup>‡</sup> Jens Martin,<sup>§</sup> and  
Amir Yacoby<sup>§</sup>

<sup>†</sup>Department of Condensed Matter Physics, Weizmann Institute of Science, Rehovot 76100, Israel, <sup>‡</sup>Departments of Physics and Electrical Engineering, University of Colorado, Denver, Colorado 80217, and <sup>§</sup>Department of Physics, Harvard University, Cambridge, Massachusetts 02138

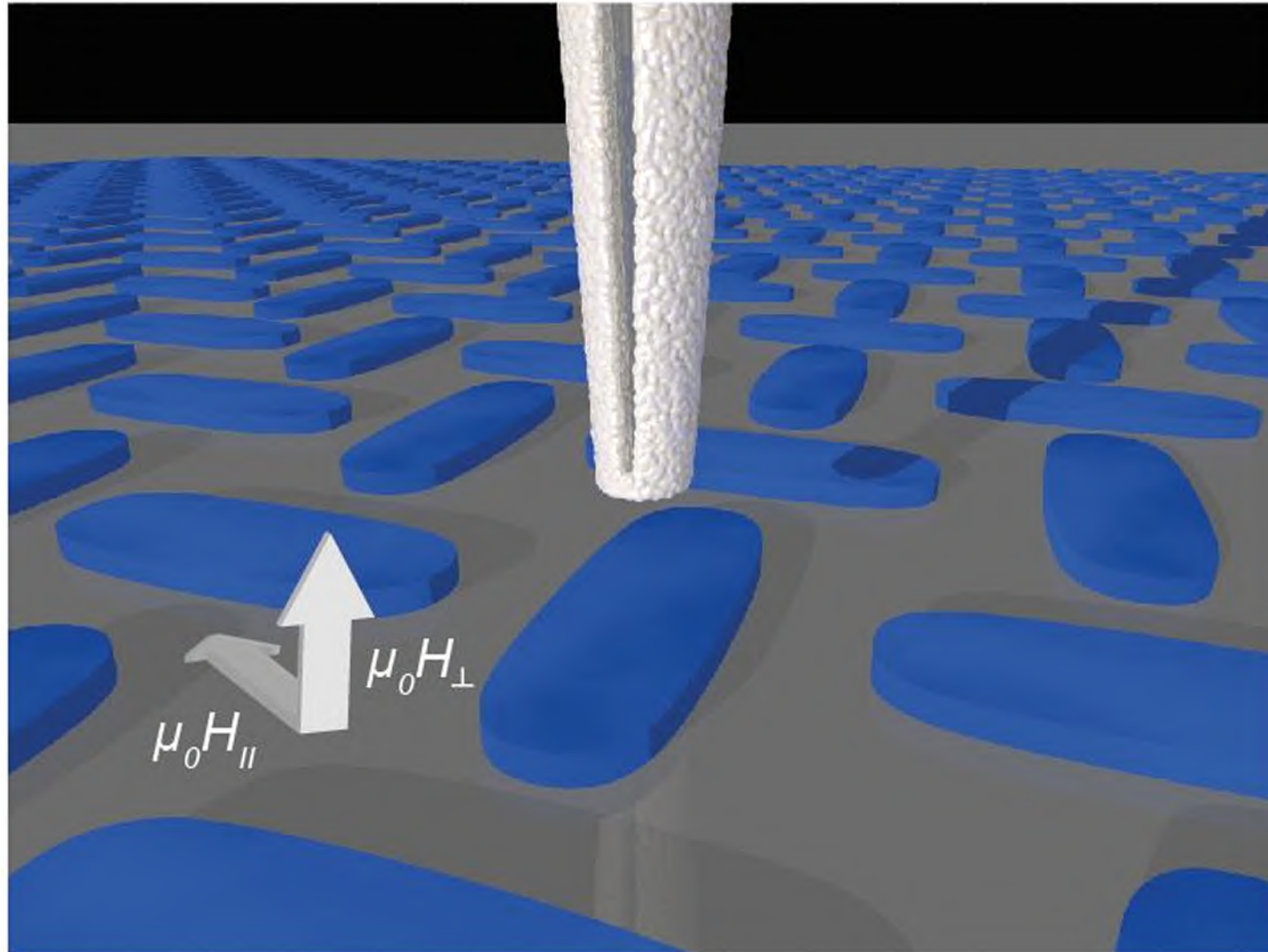


*Nano Lett.* **2010**, *10*, 1046–1049

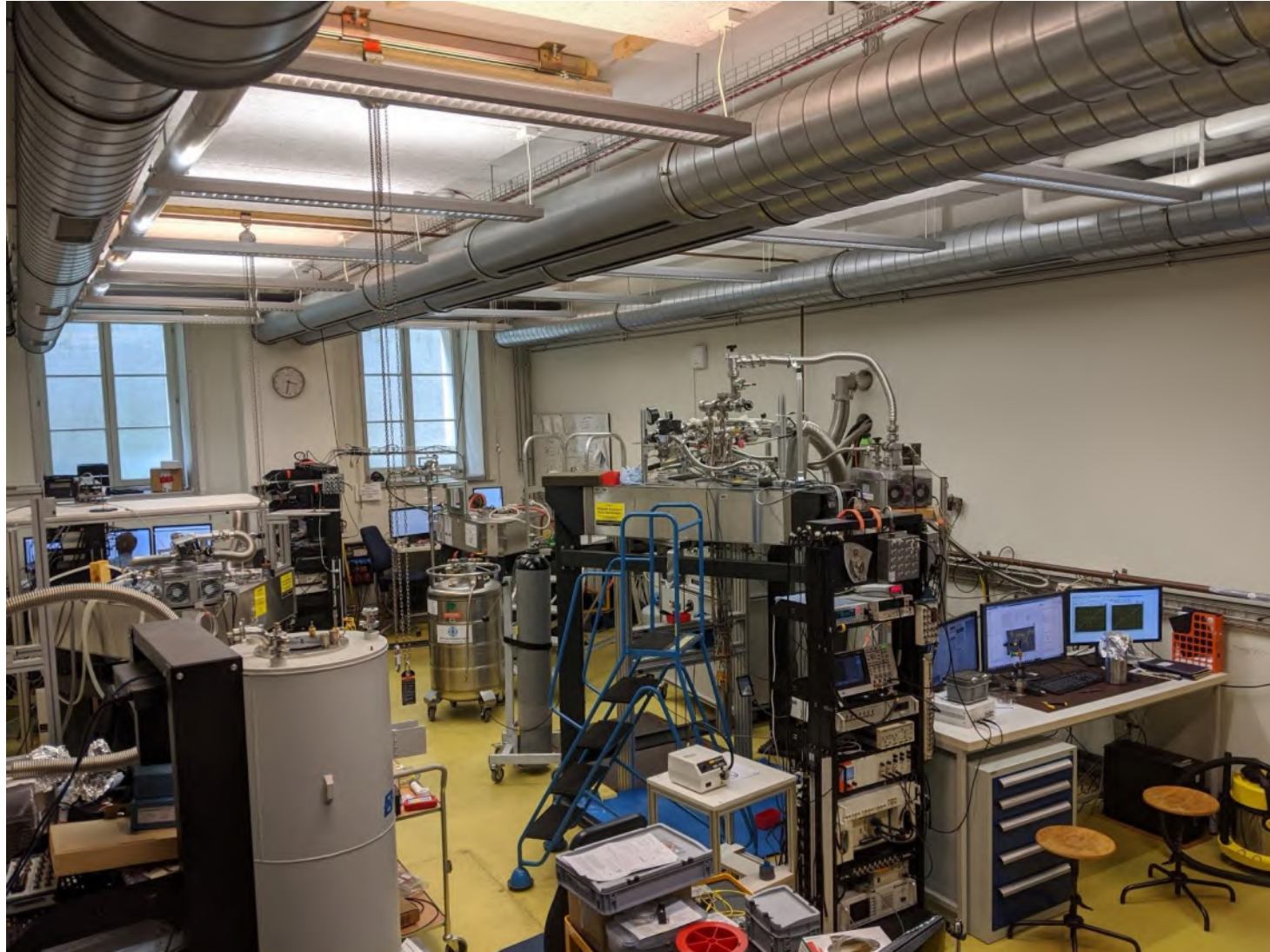
# SQUID-on-tip sensor



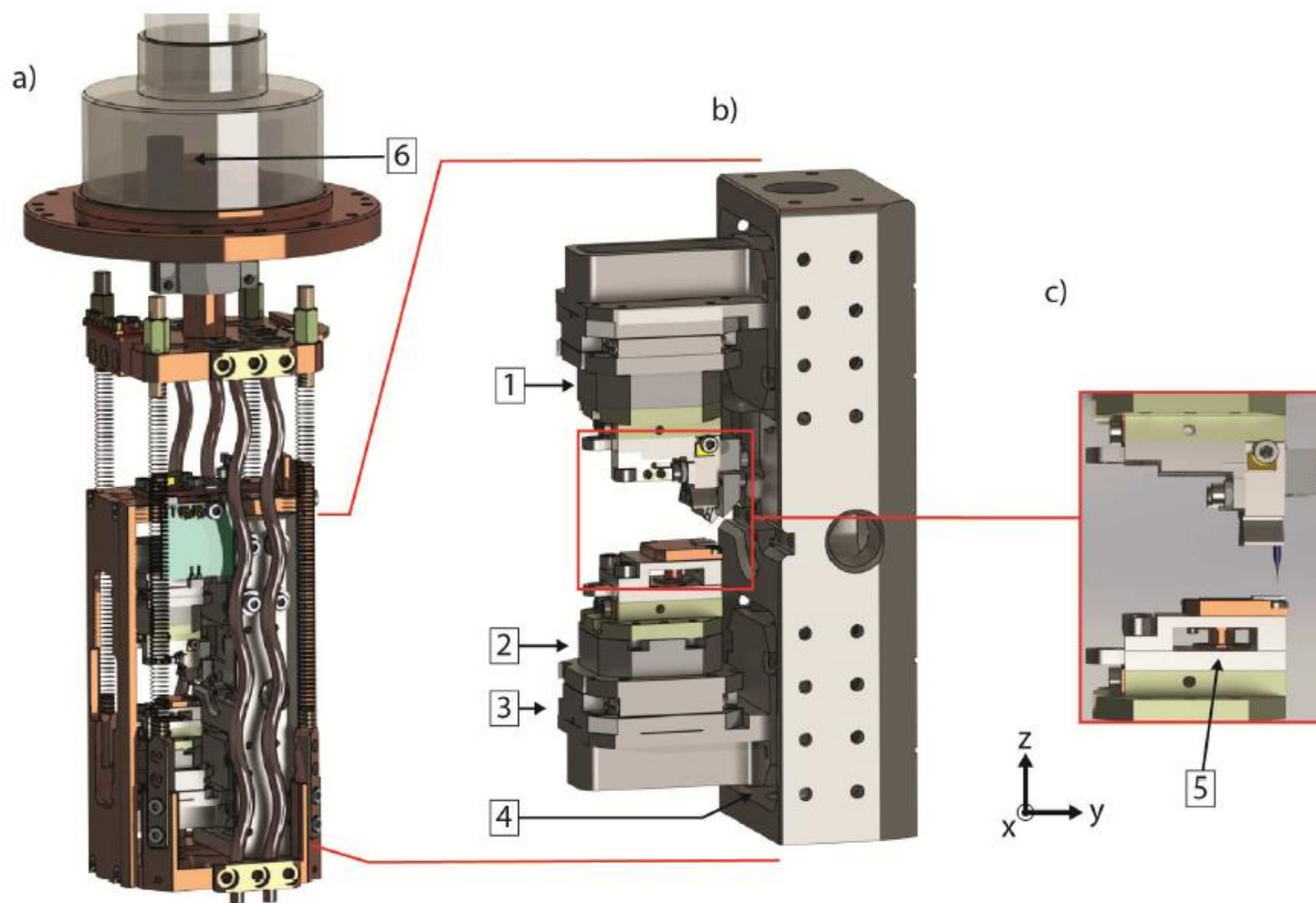
# Artificial spin ice



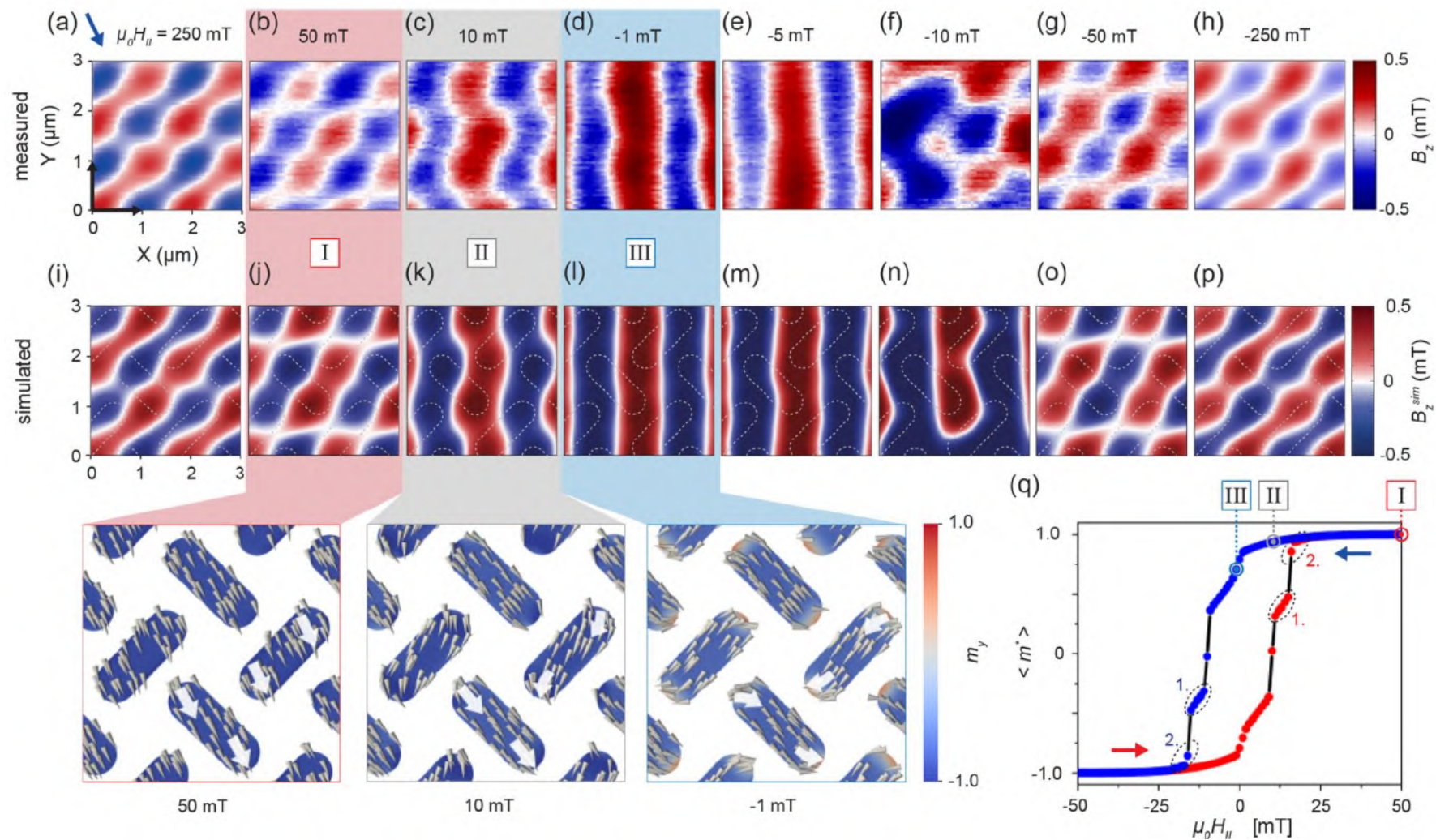
In reality...



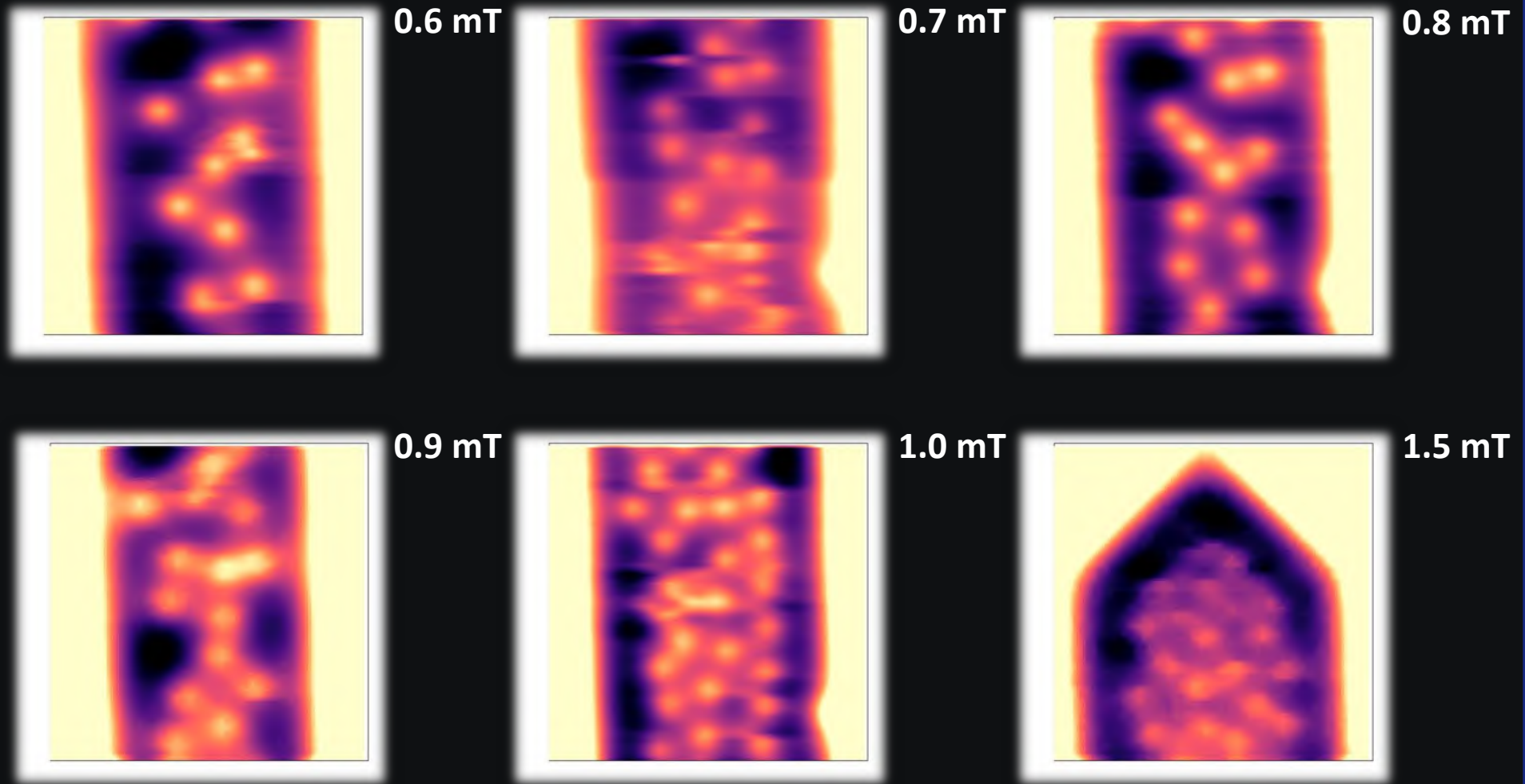
# In reality...



# Artificial spin ice

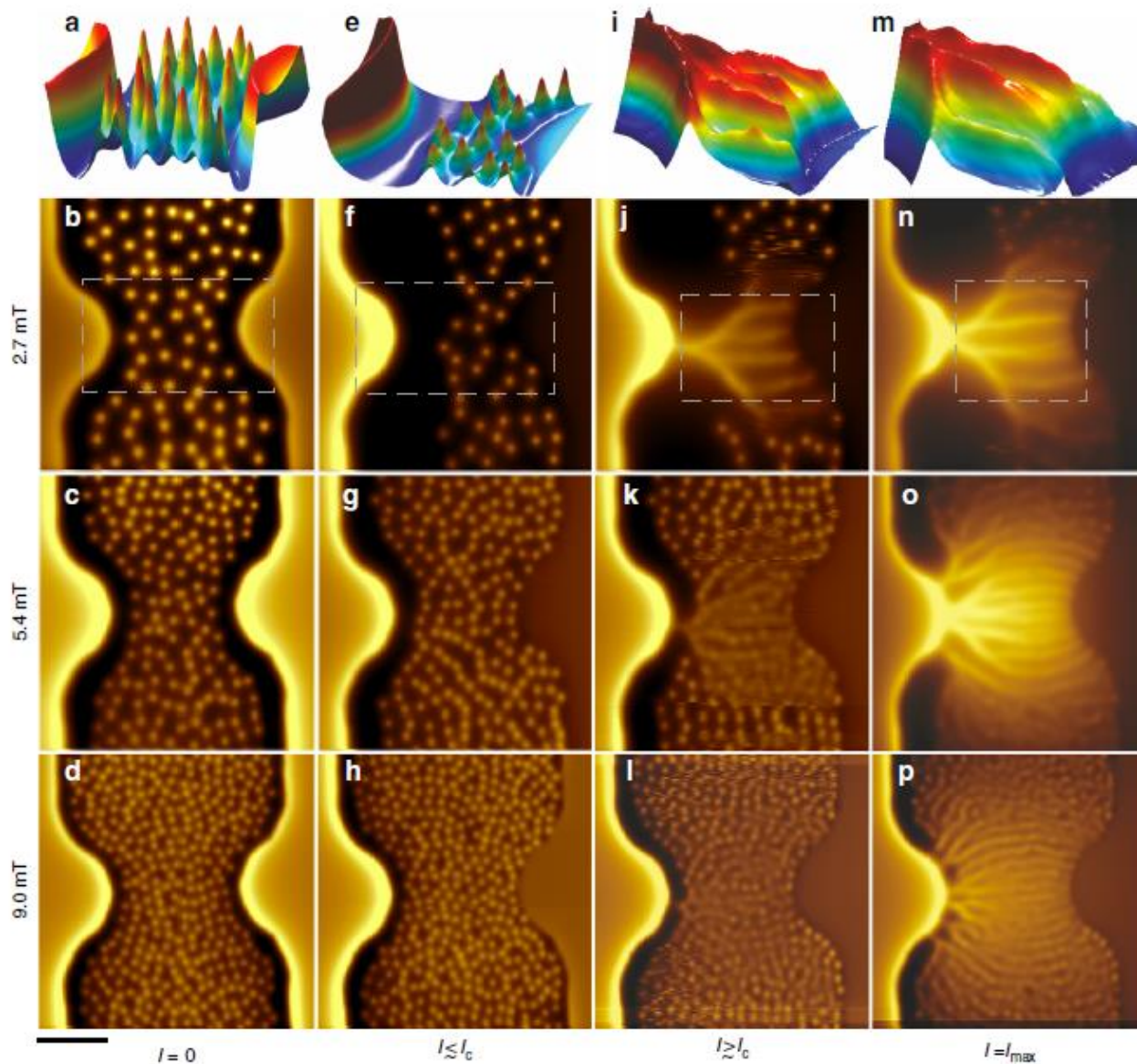


# Superconducting vortices in a MoSi thin film



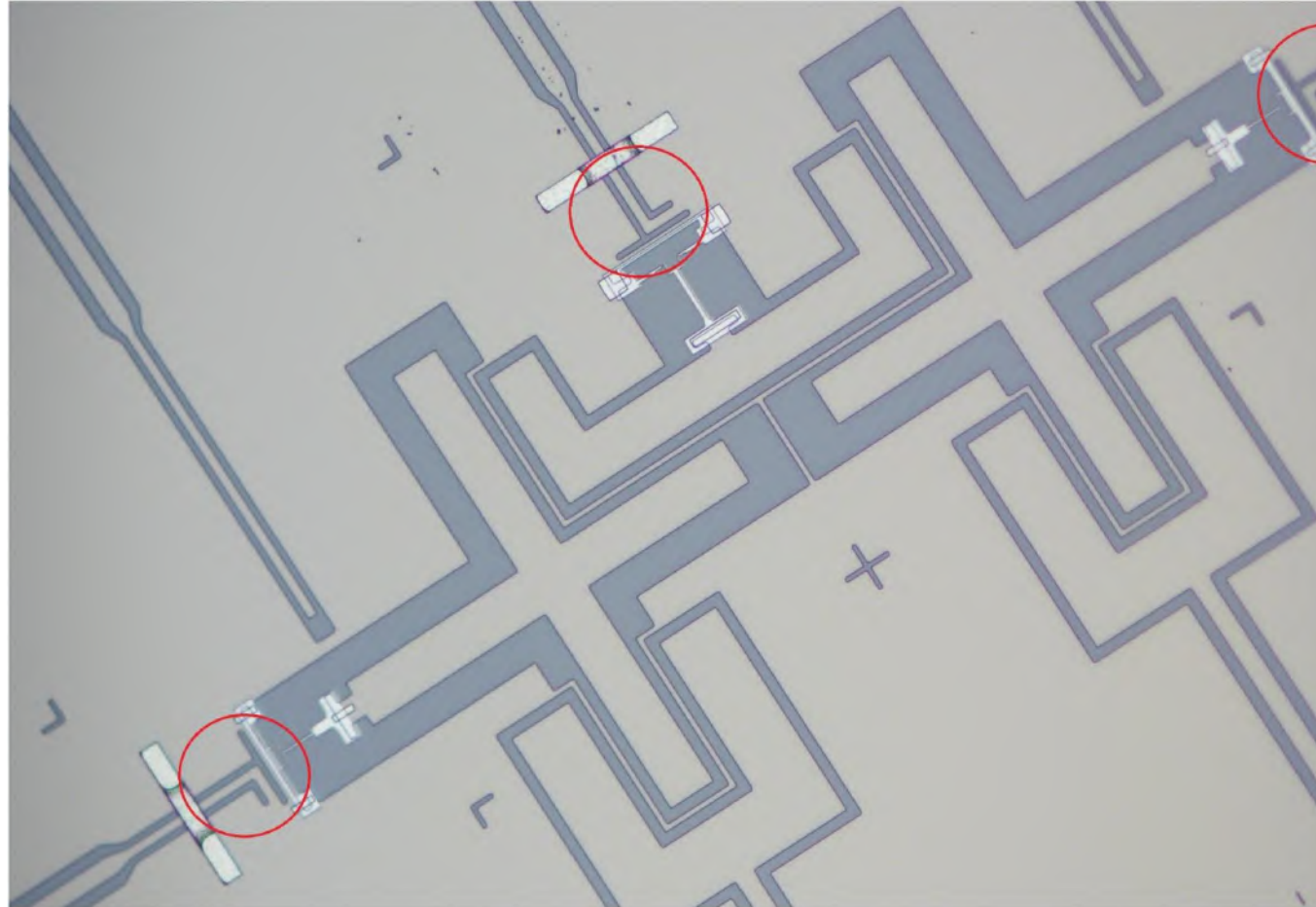
40 s per frame

# Dynamics and flow of superconducting vortices



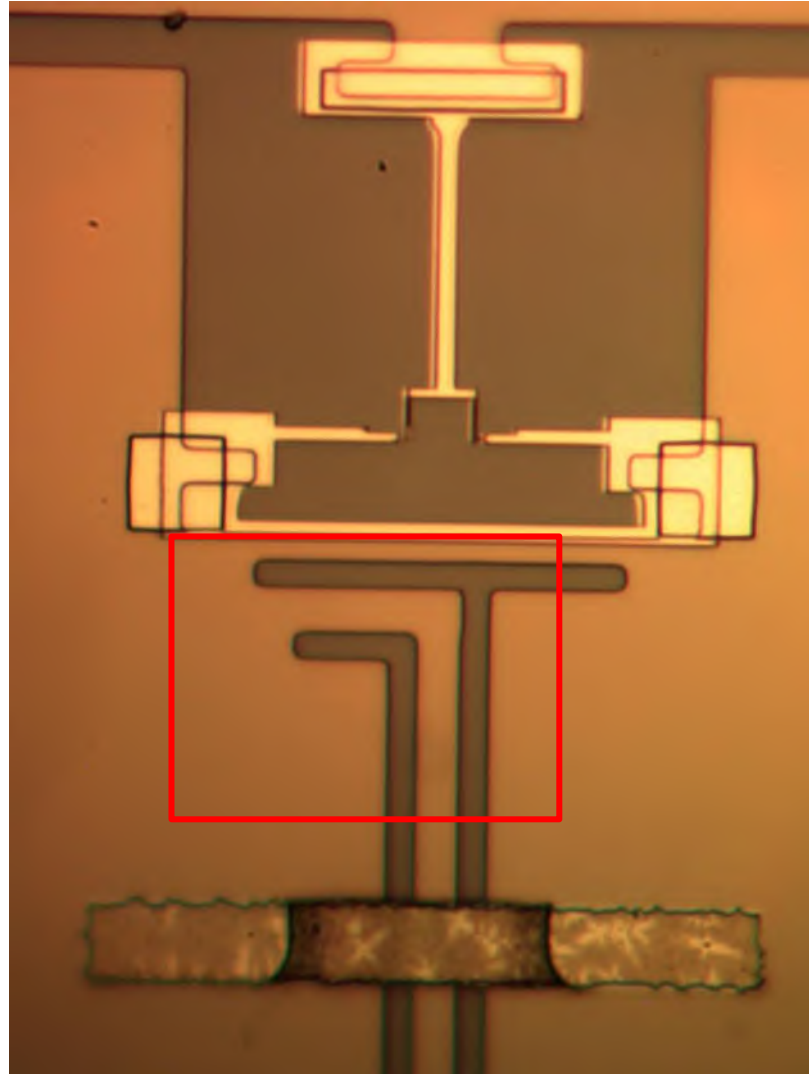
Embon et al., *Nat. Commun.* **8**, 85 (2017).

# Outlook: superconducting qubit devices



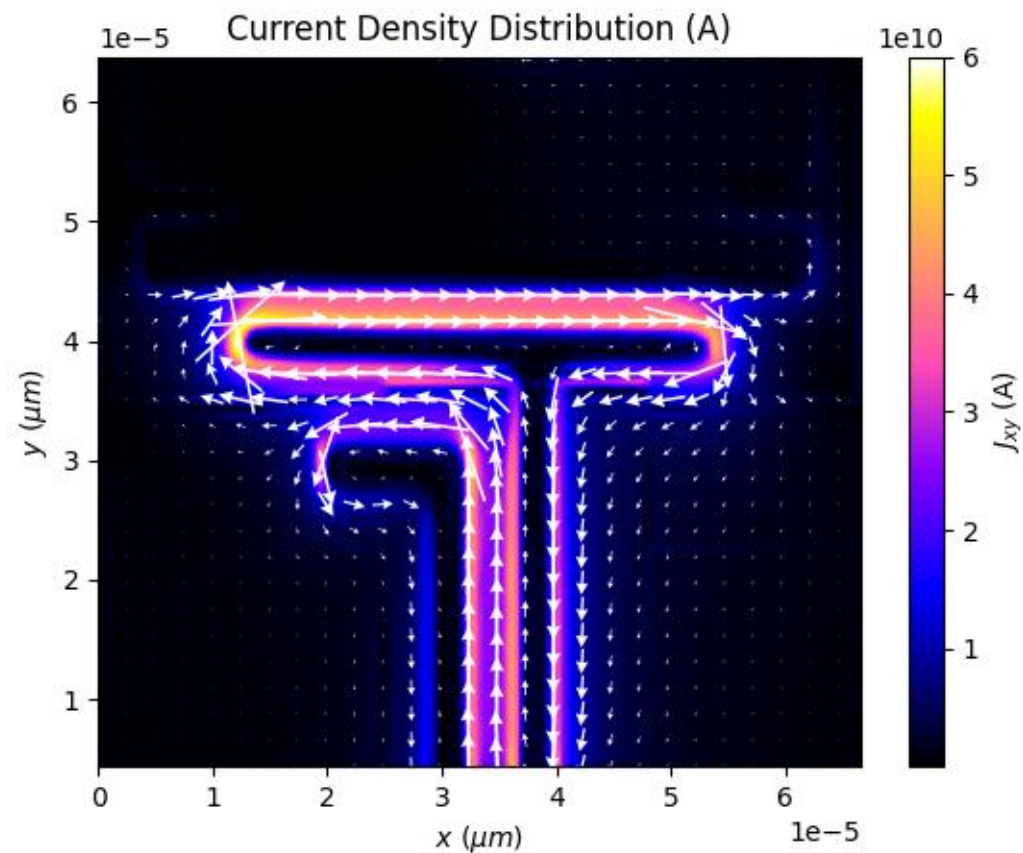
Nb qubit from Wallraff group (ETHZ).

# Outlook: superconducting qubit devices



Nb qubit from Wallraff group (ETHZ).

# Current flow in superconducting qubits



# SQUID microscopy of quantum Hall edge currents

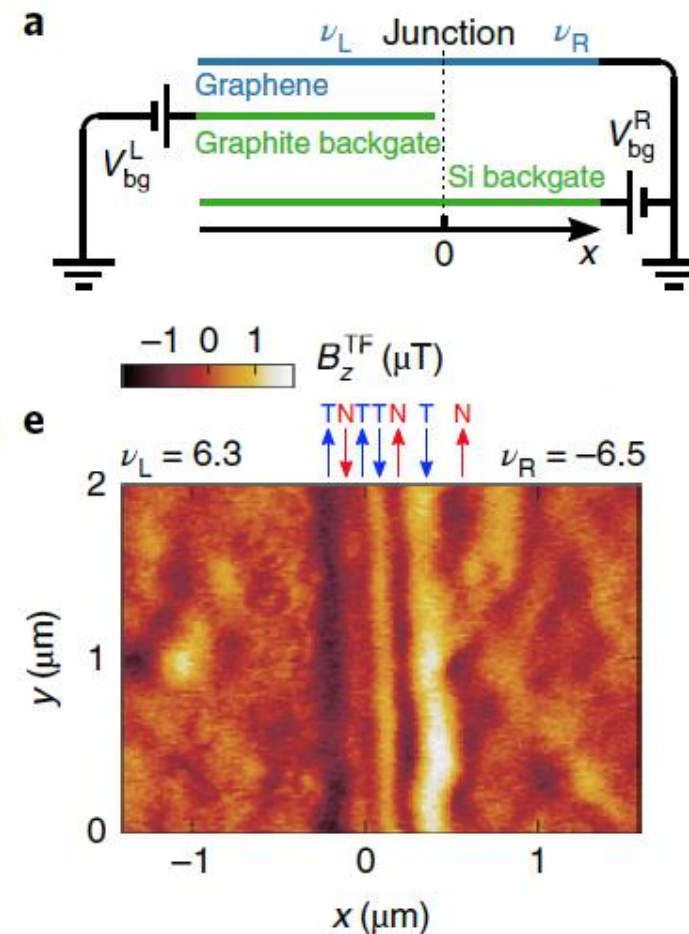
LETTERS

<https://doi.org/10.1038/s41567-019-0713-3>

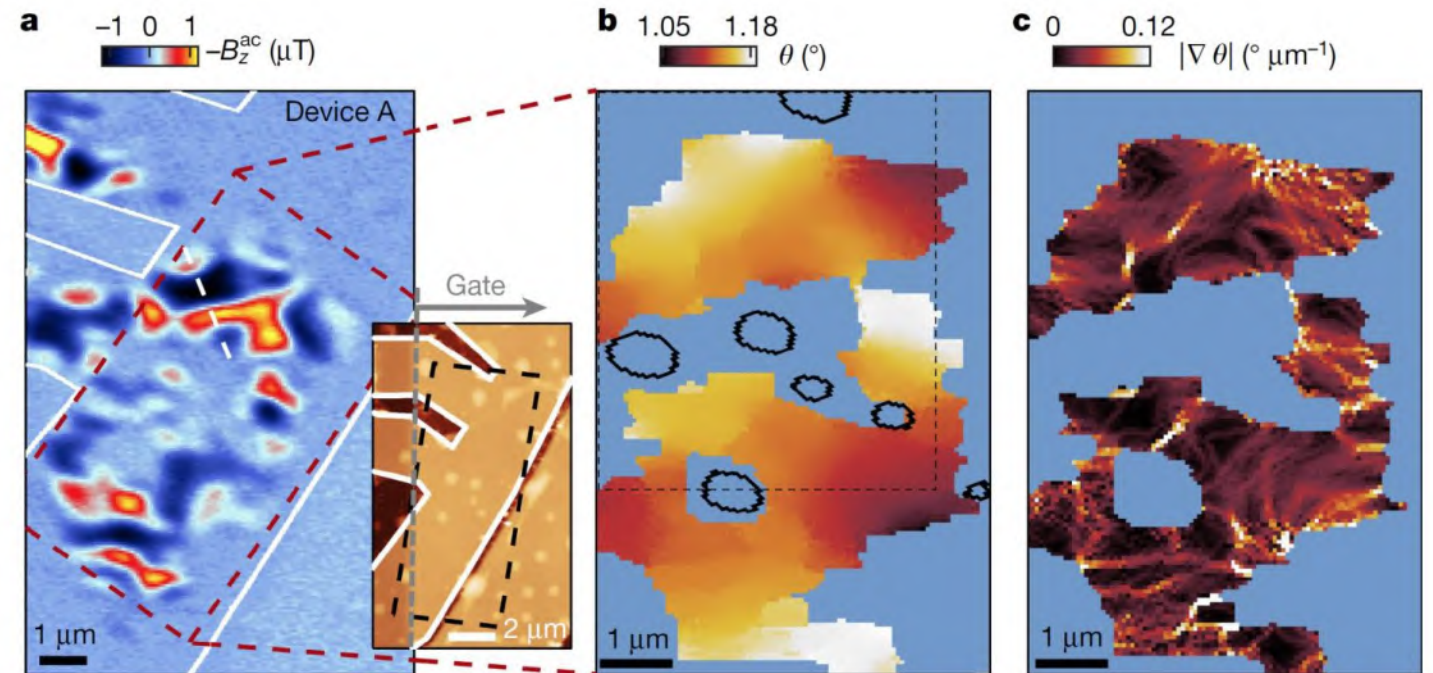
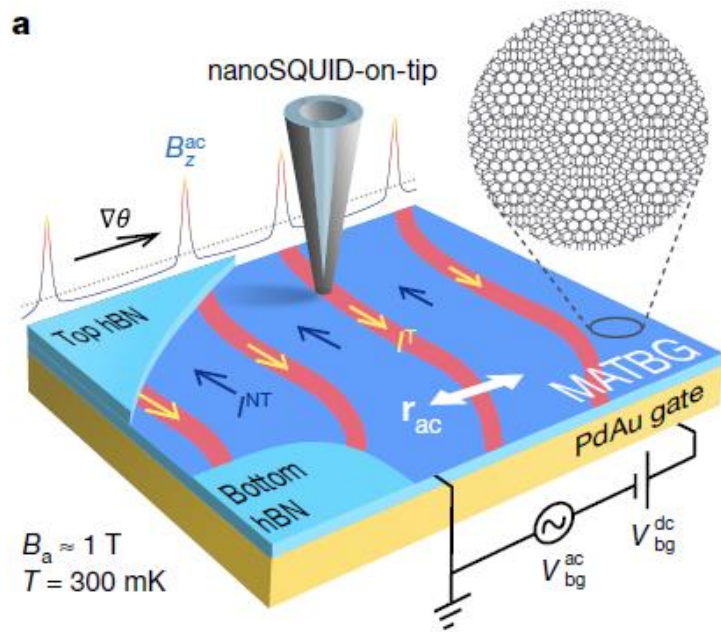
nature  
physics

## Nanoscale imaging of equilibrium quantum Hall edge currents and of the magnetic monopole response in graphene

Aviram Uri<sup>1\*</sup>, Youngwook Kim<sup>2,3</sup>, Kousik Bagani<sup>1</sup>, Cyprian K. Lewandowski<sup>4</sup>, Sameer Grover<sup>1</sup>, Nadav Auerbach<sup>1</sup>, Ella O. Lachman<sup>1,6</sup>, Yuri Myasoedov<sup>1</sup>, Takashi Taniguchi<sup>5</sup>, Kenji Watanabe<sup>5</sup>, Jurgen Smet<sup>2</sup> and Eli Zeldov<sup>1\*</sup>

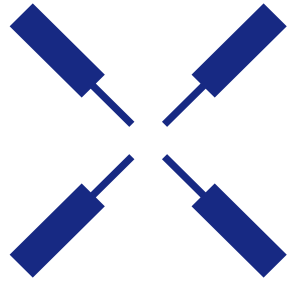


# SQUID microscopy of twist-angle disorder



# Outline

- Scanning SQUID microscopy
  - SQUID-on-tip sensors
  - Magnetic imaging with SQUID-on-tip
- Zurich Instruments lock-in amplifiers
  - Measurement principles
  - Multiple mode measurement and control
- Magnetic force microscopy
  - Scaling down the sensor
  - NW MFM
- Comparison between techniques
  - Which sensor for which application?
  - Prospects for improvement



Zurich  
Instruments

Zurich Instruments Lock-in Amplifiers  
Enabling Discovery

Jelena Trbovic, Application Scientist

# Zurich Instruments

## What do we do?



### Hardware

- Adequate speed
- High sensitivity
- Low noise
- High resolution

+

### Software

- Efficient workflows
- Functionality & features
- UI & APIs
- Value added over time



### Instruments

- Quantum control systems
- Lock-in amplifiers
- Boxcar averagers
- Impedance analyzers

# Zurich Instruments lock-in amplifiers

## Enabling discovery

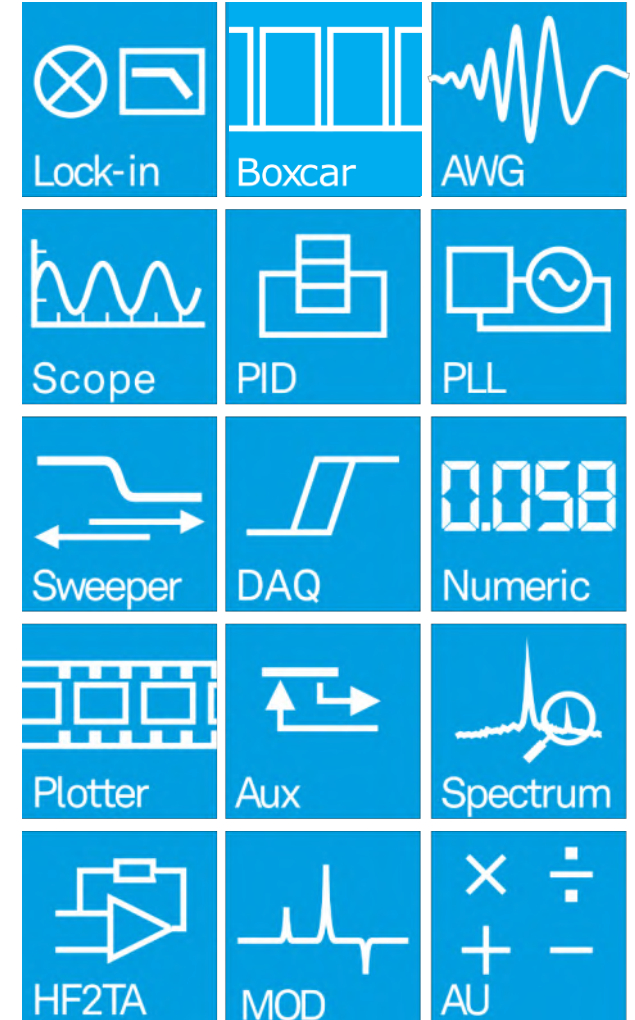
MFLI  
500 kHz/ 5 MHz

HF2LI  
50 MHz

UHFLI  
600 MHz



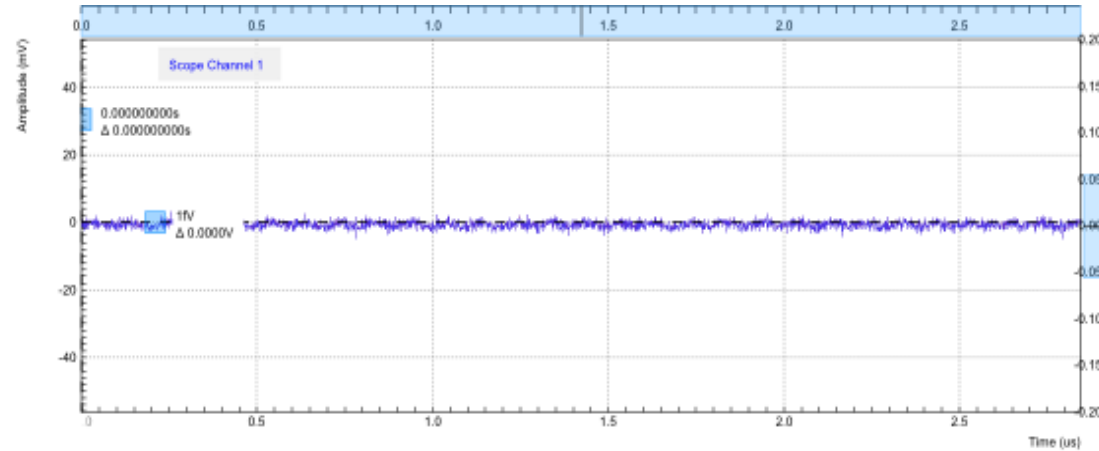
 experience  
LabOne



# Why use lock-in amplifiers?

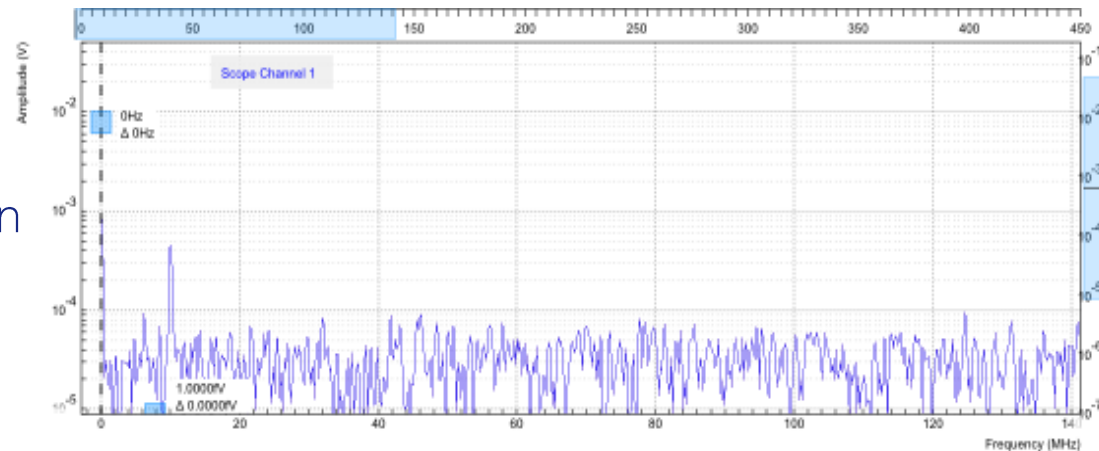
Small signals surrounded by noise are difficult to detect

Time domain



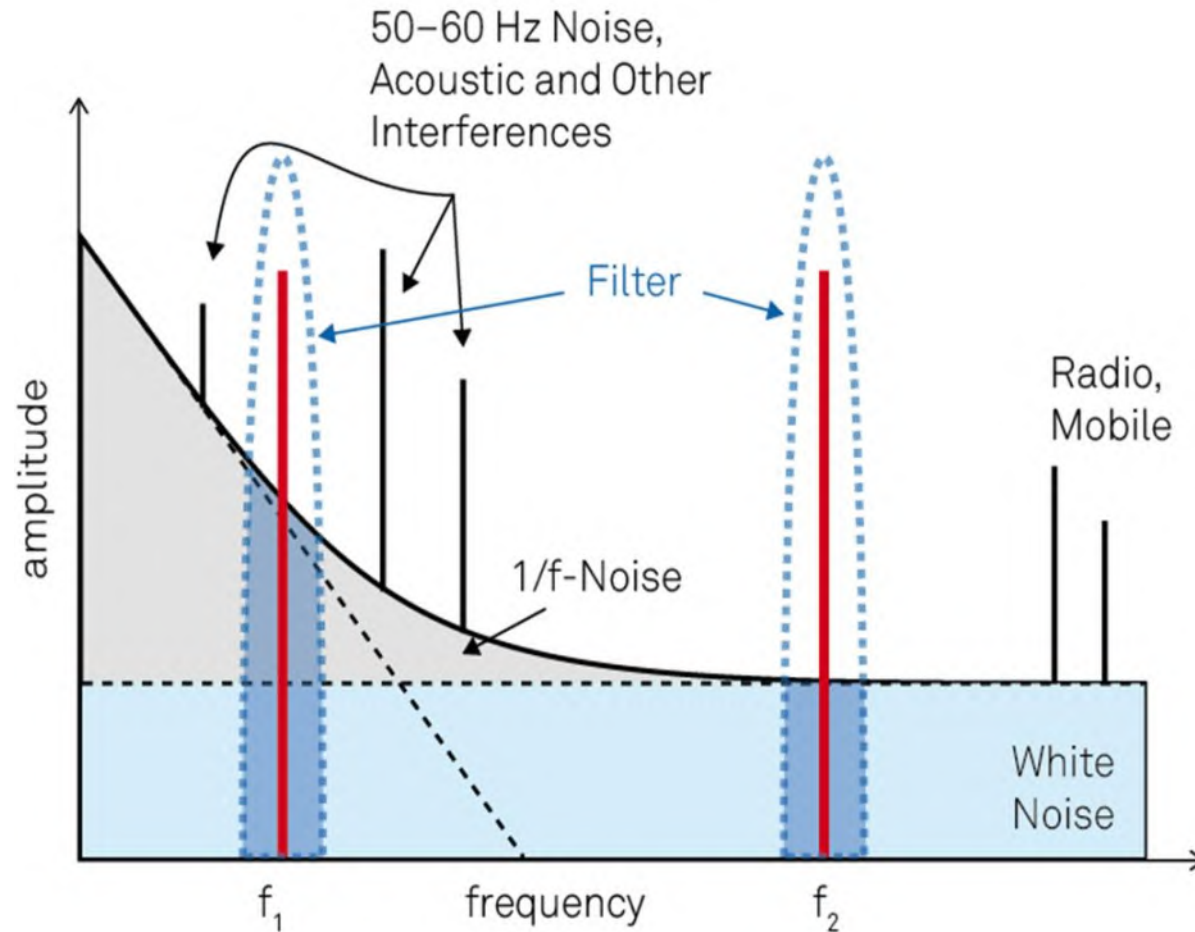
SNR ~ 10

Frequency domain

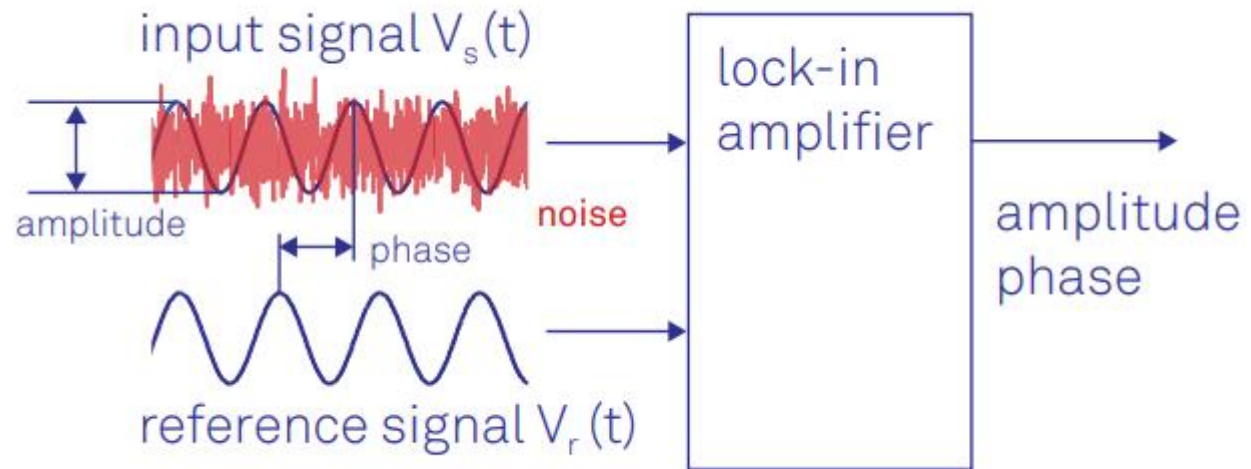


# Why use lock-in amplifiers?

## Noise spectrum



# What does lock-in amplifier measure?



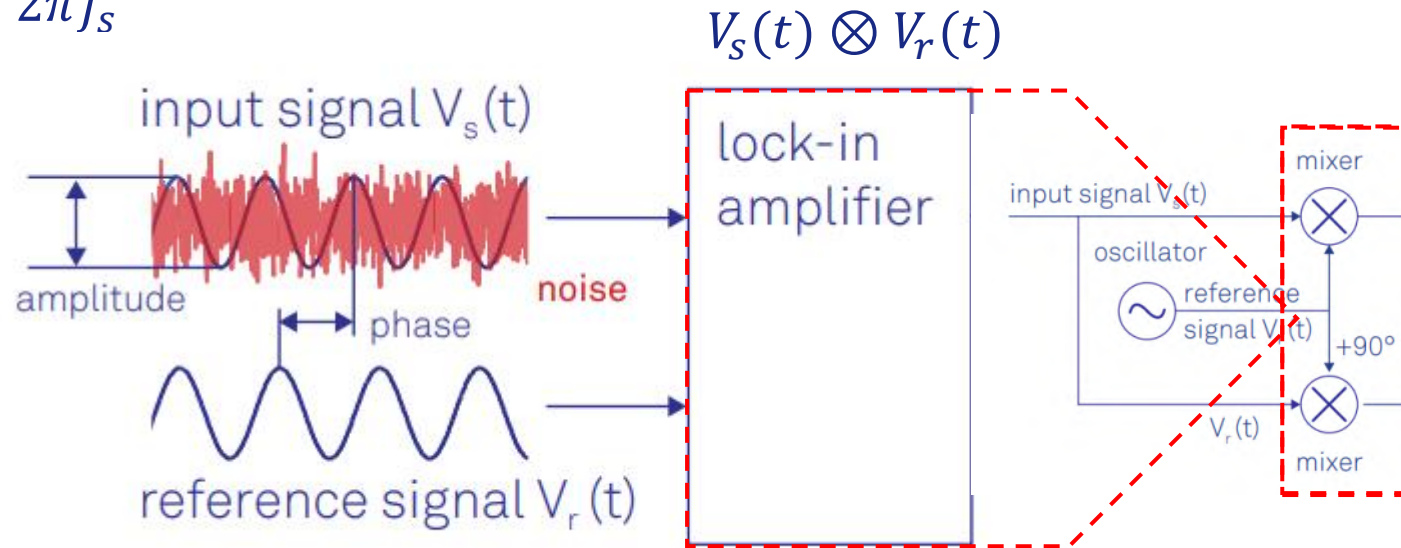
# How does lock-in amplifier measure?

## Signal amplitude and phase

### Demodulation

$$V_s(t) = V_s \sin(\omega_s t + \phi_s)$$

$$\omega_s = 2\pi f_s$$



$$\frac{V_s}{2} \cos(\phi_s) = x$$

$$\frac{V_s}{2} \sin(\phi_s) = y$$

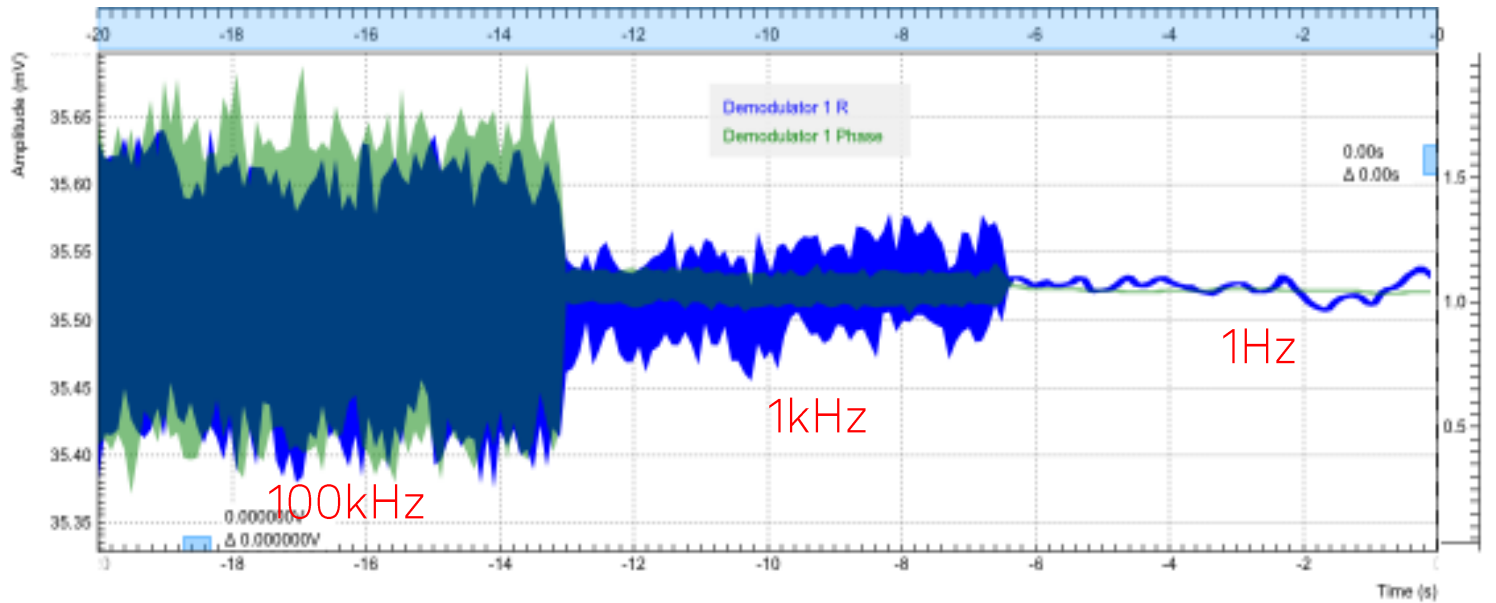
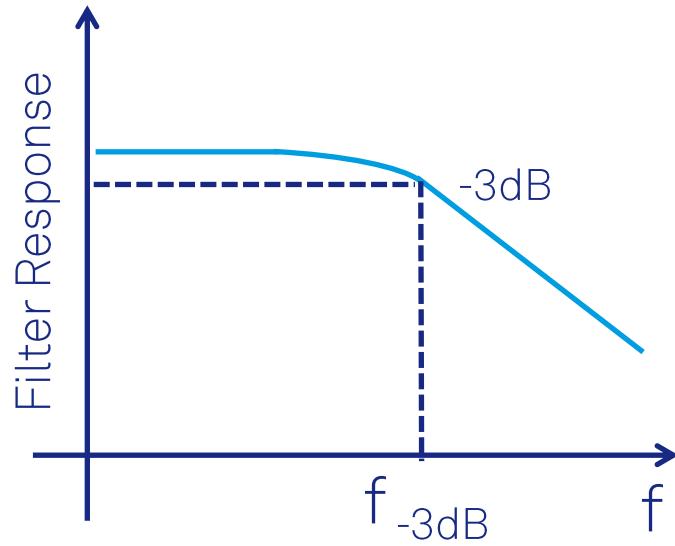
$$V_r(t)$$

$$= V_r \cos(\omega_r t + \phi_r)$$

$$\omega_r = 2\pi f_r$$

# Time constant and filter bandwidth

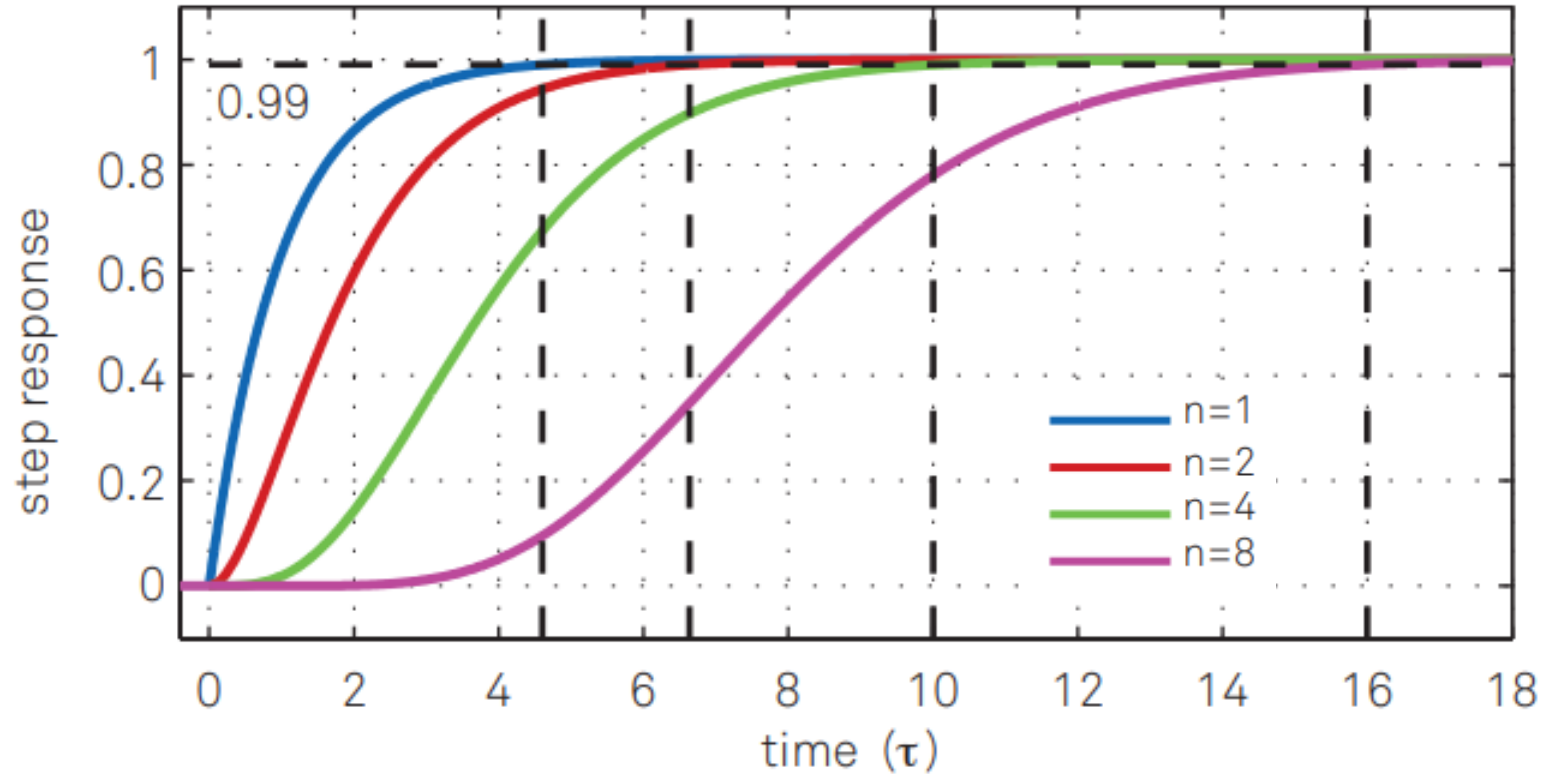
$$\tau_C = 1/2\pi f_{-3dB}$$



Reducing filter BW  $\rightarrow$  increase time constant  
Slower measurements  $\rightarrow$  less noise

# Filter settling time

## Higher filter orders



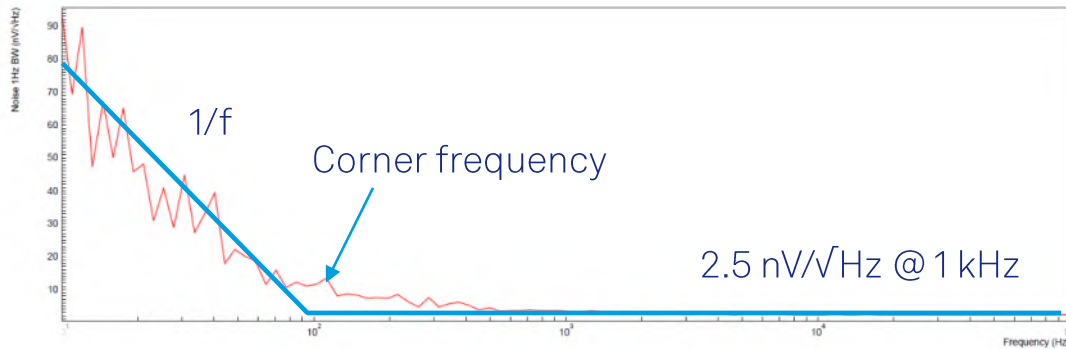
The higher the filter order, the longer it takes for the filter to settle.  
Early data sampling leads to erroneous results.

# Instrument related noise

## The lower the better

### Input noise

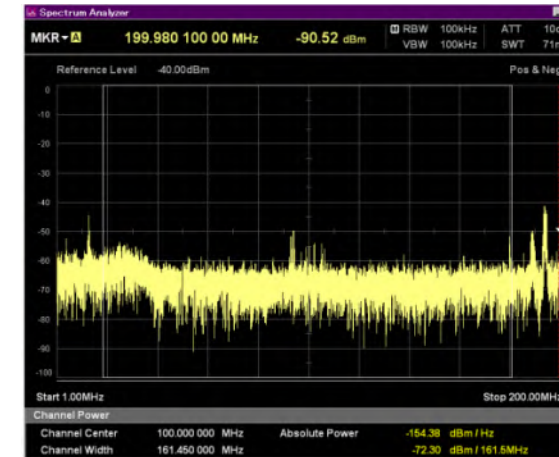
→ The sum of all the noise sources internal to the instrument, referenced to the signal input



MFLI Input noise density as a function of frequency

### Noise dissipated from input ports

→ Noise dissipated from input ports can be absorbed by the system resulting in an increased electronic temperature



Dissipated noise from MFLI voltage input in the frequency range 10 MHz – 200 MHz

# MFLI basic unit

- 1 dual-phase demodulator
- 1 external reference
- Single frequency measurement
- Choice between V or I measurement



Config x Device x Aux x Lock-in x

All

1

### Signal Inputs

**Voltage Input 1**

Range 1.0 V / V

Scaling 1.0

AC  50  $\Omega$   Diff  Float

**Current Input 1**

Range 10.0m A / A

Scaling 1.0

Float

### Oscillators

Mode	Frequency (Hz)
1 Manual	100.00000000k

### Demodulators

Reference Mode	Osc	Harm	Demod Freq (Hz)	Phase (deg)	Input Signal	Low-Pass Filters Order	Low-Pass Filters BW 3 dB	Low-Pass Filters Sinc	Data Transfer En	Data Transfer Rate (Sa/s)	Trigger	Trig Mode
1 Manual	1	1	100.00000000k	0.000	Sig In 1	3	99.51	<input type="radio"/>	<input checked="" type="radio"/>	1.674k	Continuous	
2 Manual	1	1	100.00000000k	0.000	Sig In 1	3	99.51	<input type="radio"/>	<input type="radio"/>			

### Signal Outputs

**Output 1**

On  50  $\Omega$

Range 1V

Offset (V) 0.000 Sine

Amp (Vpk) 500.0m

Add  Diff

# MFLI with MF-MD Multi-demodulator Option

- 4 dual-phase demodulators
- 2 external references
- Simultaneous measurements at 4 different frequencies
- Simultaneous measurements of 3 higher harmonics
- Simultaneous V and I measurements



Config x Device x Aux x Lock-in x

All

**Signal Inputs**

1 Voltage Input 1  
Range 3.0m  
Scaling 1.0 V / V

2 AC 50 Ω Diff  
Float

3 Current Input 1  
Range 1.0n  
Scaling 1.0 A / A  
Float

4

**Oscillators**

Mode	Frequency (Hz)
1 Manual	100.00000000k
2 Manual	100.00000000k
3 Manual	100.00000000k
4 Manual	100.00000000k

**Demodulators**

Reference Mode	Frequencies Osc	Harm	Demod Freq (Hz)	Phase (deg)	Input Signal	Low-Pass Filters Order	TC	Sinc	Data Transfer En Rate (Sa/s)	Trigger	Trig Mode
1 Manual	1	1	100.00000000k	0.000	Sig In 1	3	100.0m	0	1.674k	Continuous	
2 Manual	1	1	100.00000000k	0.000	Curr In 1	3	100.0m	0	1.674k	Continuous	
3 Manual	2	1	100.00000000k	0.000	Sig In 1	3	100.0m	0	1.674k	Continuous	
4 Manual	2	1	100.00000000k	0.000	Curr In 1	3	100.0m	0	1.674k	Continuous	

**Output Amplitudes**

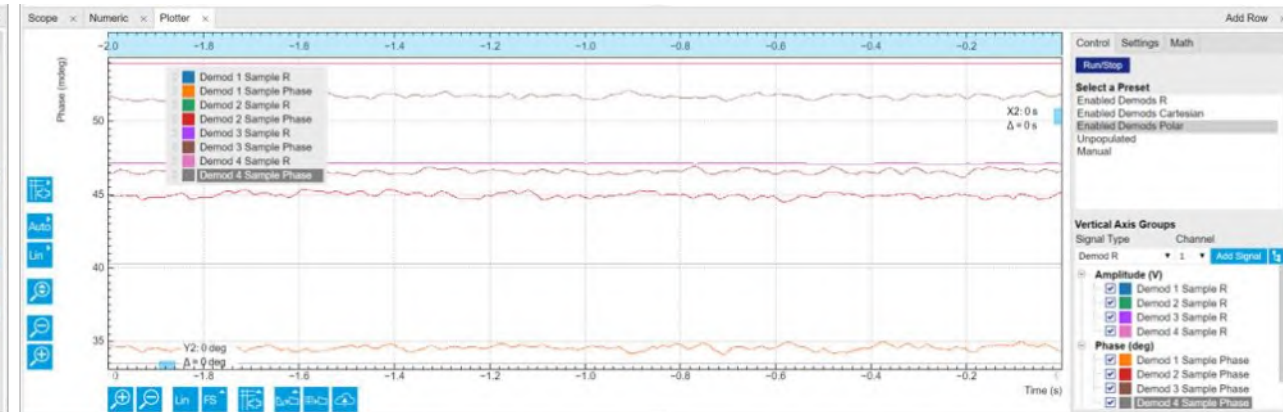
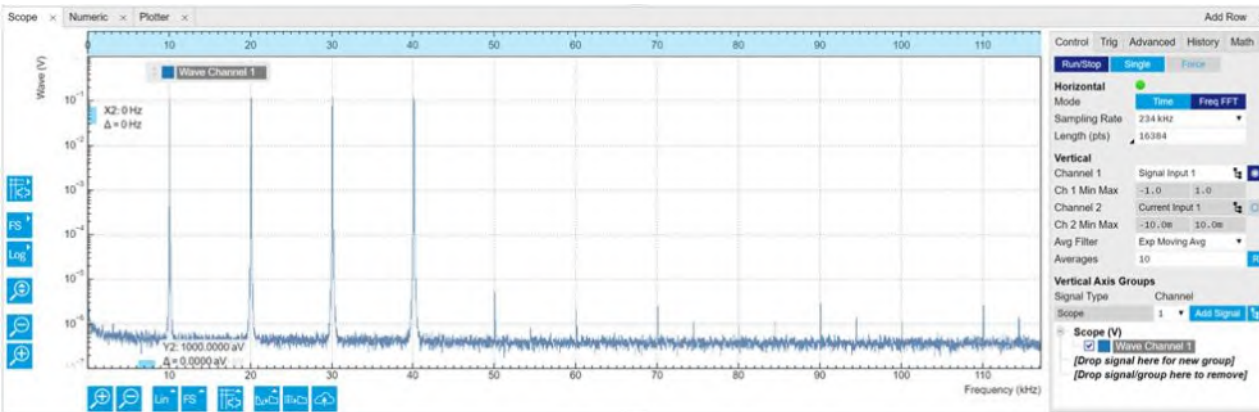
Mode	Amp 1 (Vpk)
1 Sine	10.00m
2 Sine	10.00m
3 Sine	10.00m
4 Sine	1.007m

**Signal Outputs**

Output 1  
On 50 Ω  
Range 10 mV  
Offset (V) 0.000  
Add Diff

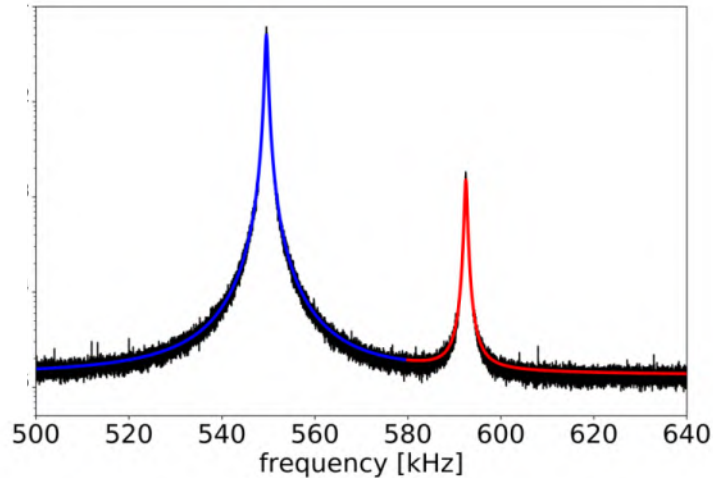
# MFLI with MF-MD Multi-demodulator Option

- 4 dual-phase demodulators
- 2 external references
- Simultaneous measurements at 4 different frequencies
- Simultaneous measurements of 3 higher harmonics
- Simultaneous V and I measurements



# MFLI with MD Multi-demodulator Option

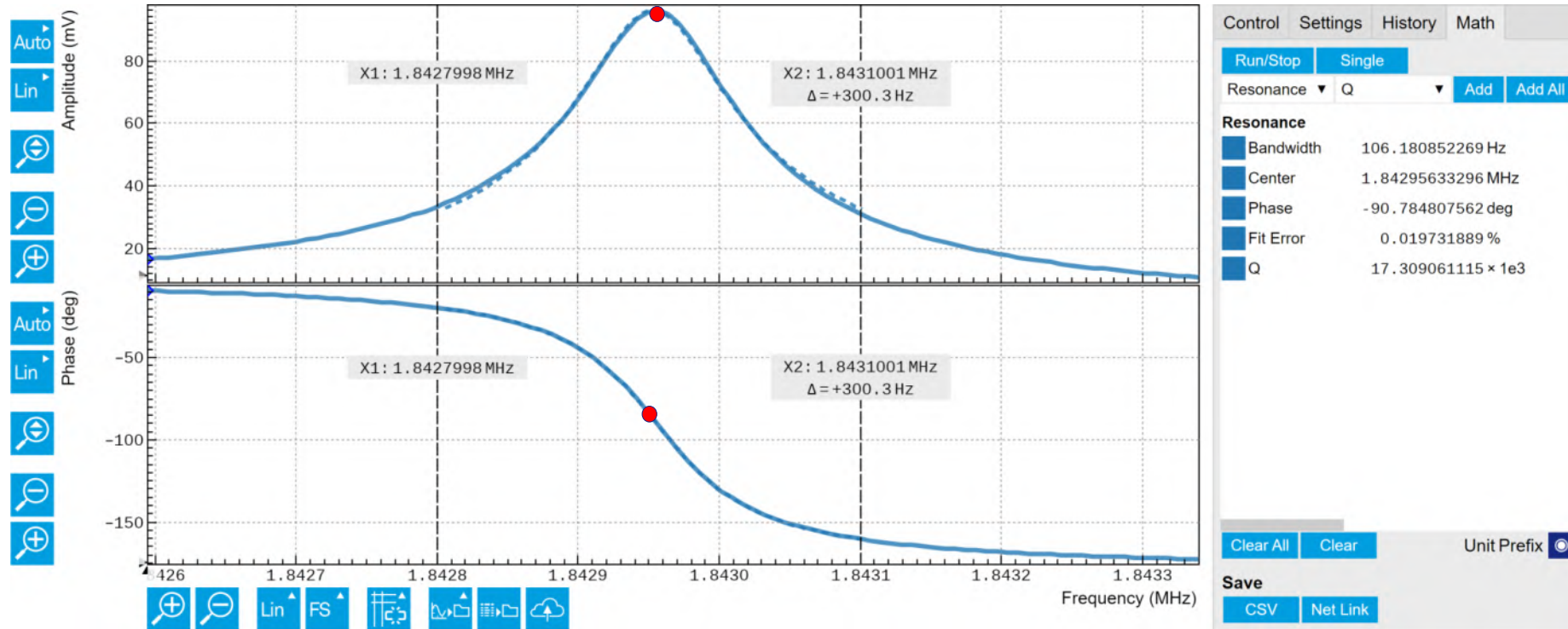
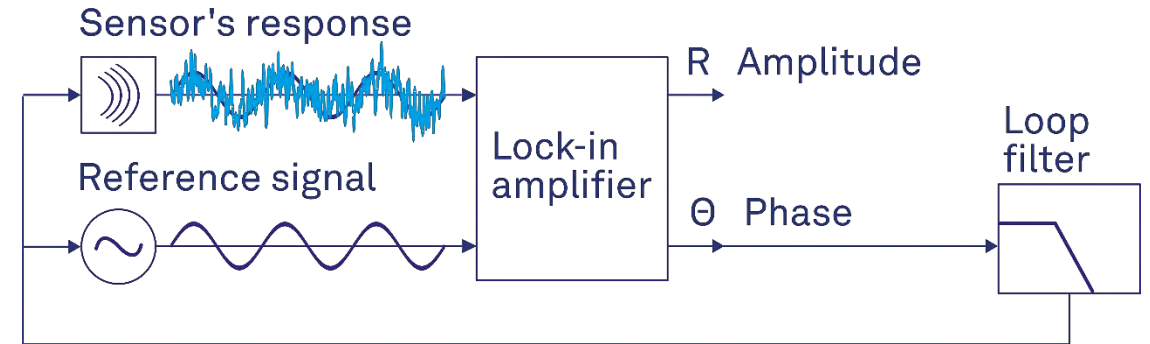
- 4 dual-phase demodulators
- 2 external references
- Simultaneous measurements at 4 different frequencies
- Simultaneous measurements of 3 higher harmonics
- Simultaneous V and I measurements



# Sensor control and readout

## Resonance amplitude and phase characterization

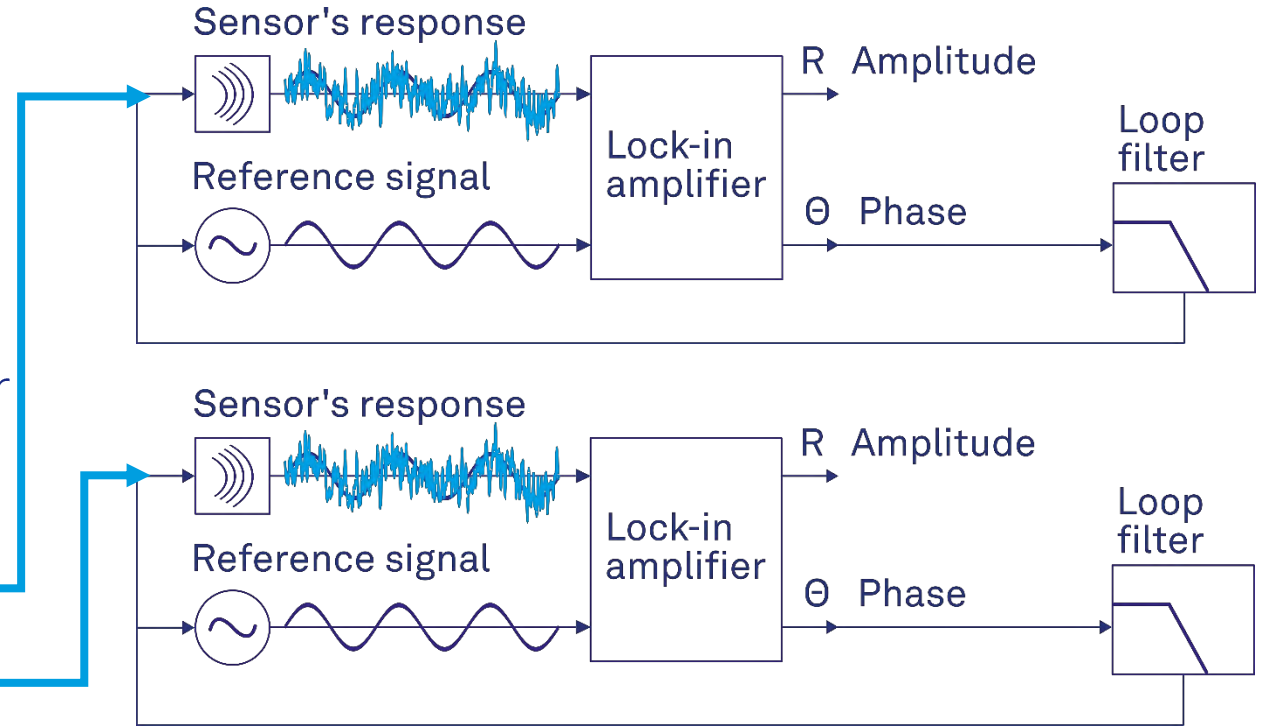
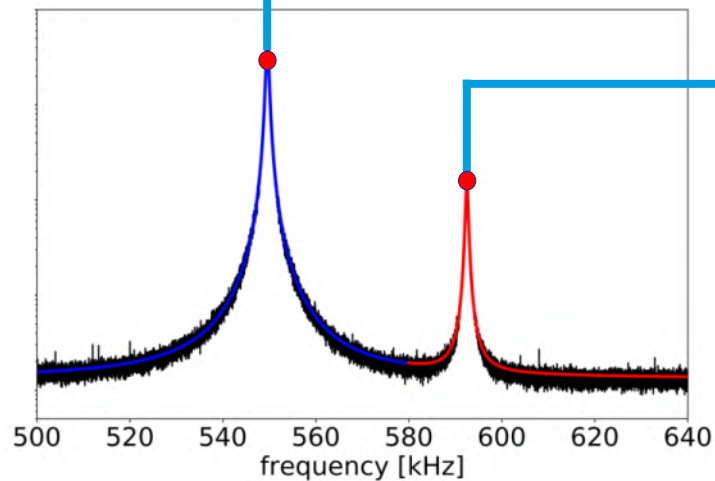
- Frequency sweep
- Determine resonator characteristics
- Use the phase at the resonance as a set point for the phase-locked loop (PLL)



# Feedback control loops with MF-PID and MF-MD options

## Dual phase-locked loop (PLL)

- The lock-in measures 2 amplitudes and 2 phases
- Compares with setpoints and generates the error signal
- PLL controller adjusts the numerical oscillator frequency to minimize the error
- The frequency shift corresponds to the external magnetic field component



# Magnetic sensors characterization and control

## All in one.

### Your benefits

- Simplify your setup with a single instrument for concurrent characterization and control
- Measure multiple signals simultaneously with the MF-MD Option
- Track and control multiple resonances simultaneously with the MF-PID Option



# Outline

- Scanning SQUID microscopy
  - SQUID-on-tip sensors
  - Magnetic imaging with SQUID-on-tip
- Zurich Instruments lock-in amplifiers
  - Measurement principle
  - Multiple mode measurement and control
- Magnetic force microscopy
  - Scaling down the sensor
  - NW MFM
- Comparison between techniques
  - Which sensor for which application?
  - Prospects for improvement

## Magnetic imaging by “force microscopy” with 1000 Å resolution

Y. Martin and H. K. Wickramasinghe

*IBM T. J. Watson Research Center, P. O. Box 218, Yorktown Heights, New York 10598*

(Received 19 December 1986; accepted for publication 19 March 1987)

We describe a new method for imaging magnetic fields with 1000 Å resolution. The technique is based on using a force microscope to measure the magnetic force between a magnetized tip and the scanned surface. The method shows promise for the high-resolution mapping of both static and dynamic magnetic fields.

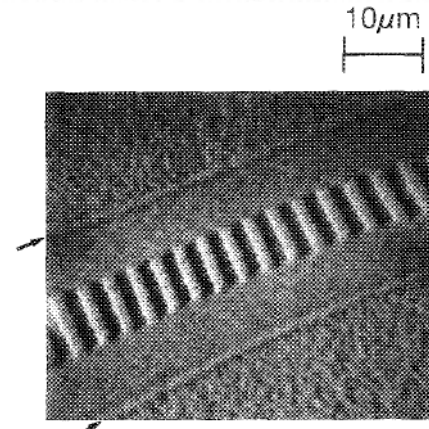
*Appl. Phys. Lett.* **50** (20), 18 May 1987

## Magnetic force microscopy: General principles and application to longitudinal recording media

D. Rugar, H. J. Mamin, P. Guethner,<sup>a)</sup> S. E. Lambert,<sup>b)</sup> J. E. Stern,<sup>c)</sup> I. McFadyen,<sup>b)</sup> and T. Yogi<sup>b)</sup>

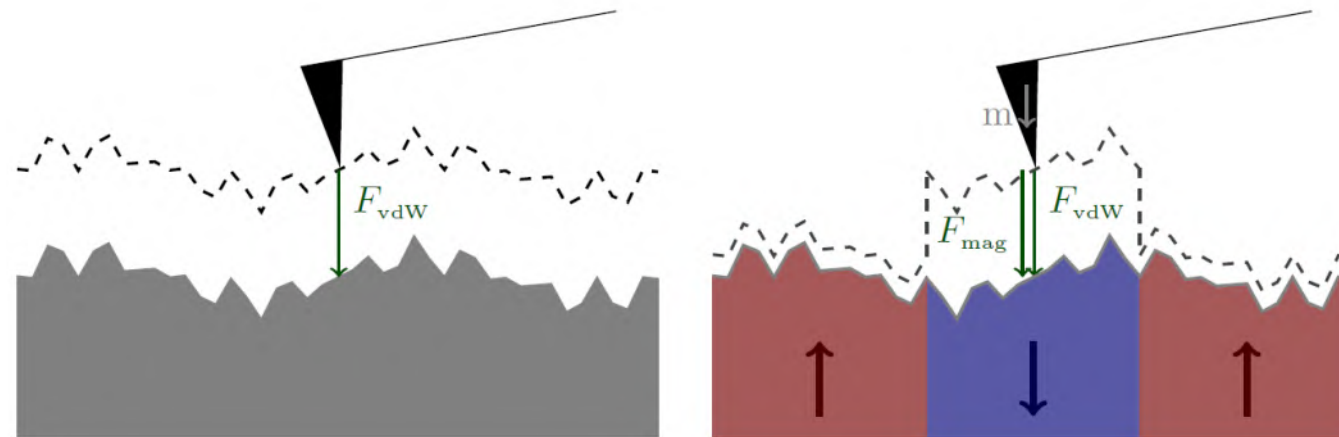
*IBM Research Division, Almaden Research Center, 650 Harry Road, San Jose, California 95120-6099*

(Received 15 January 1990; accepted for publication 13 April 1990)

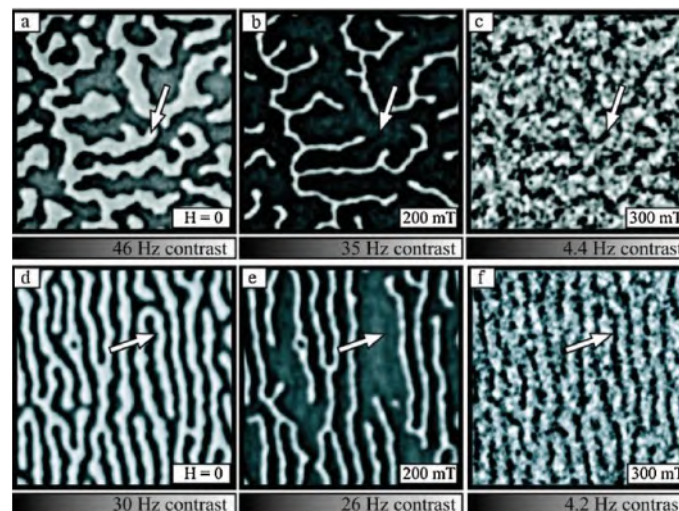


*J. Appl. Phys.* **68** (3), 1 August 1990

# MFM achieves down to 10 nm resolution



Schwenk, *Ph.D. Thesis in Physics*, University of Basel (2016).



Schmid et al., *Phys. Rev. Lett.* **105**, 197201 (2010).

$$S_F = 4 k_B T \Gamma$$

$$\Gamma = \frac{m\omega_0}{Q} \quad \frac{dE}{dt} = -\Gamma \dot{x}^2$$

Amplitude measurement:

$$F_{min} = \sqrt{4 k_B T \Gamma}$$

$$\tau_{min} = l_e \sqrt{4 k_B T \Gamma}$$

Frequency measurement:

$$\left(\frac{\partial F}{\partial x}\right)_{min} = \frac{1}{x_{osc}} \sqrt{4 k_B T \Gamma}$$

$$\left(\frac{\partial \tau}{\partial \theta}\right)_{min} = \frac{l_e}{\theta_{osc}} \sqrt{4 k_B T \Gamma}$$

100  $\mu\text{m}$



$$S_F = 4 k_B T \Gamma$$

$$\Gamma = \frac{m \omega_0}{Q} \quad \frac{dE}{dt} = -\Gamma \dot{x}^2$$

$$m \propto w t l \quad \omega_0 \propto \frac{t}{l^2} \quad Q \propto t$$

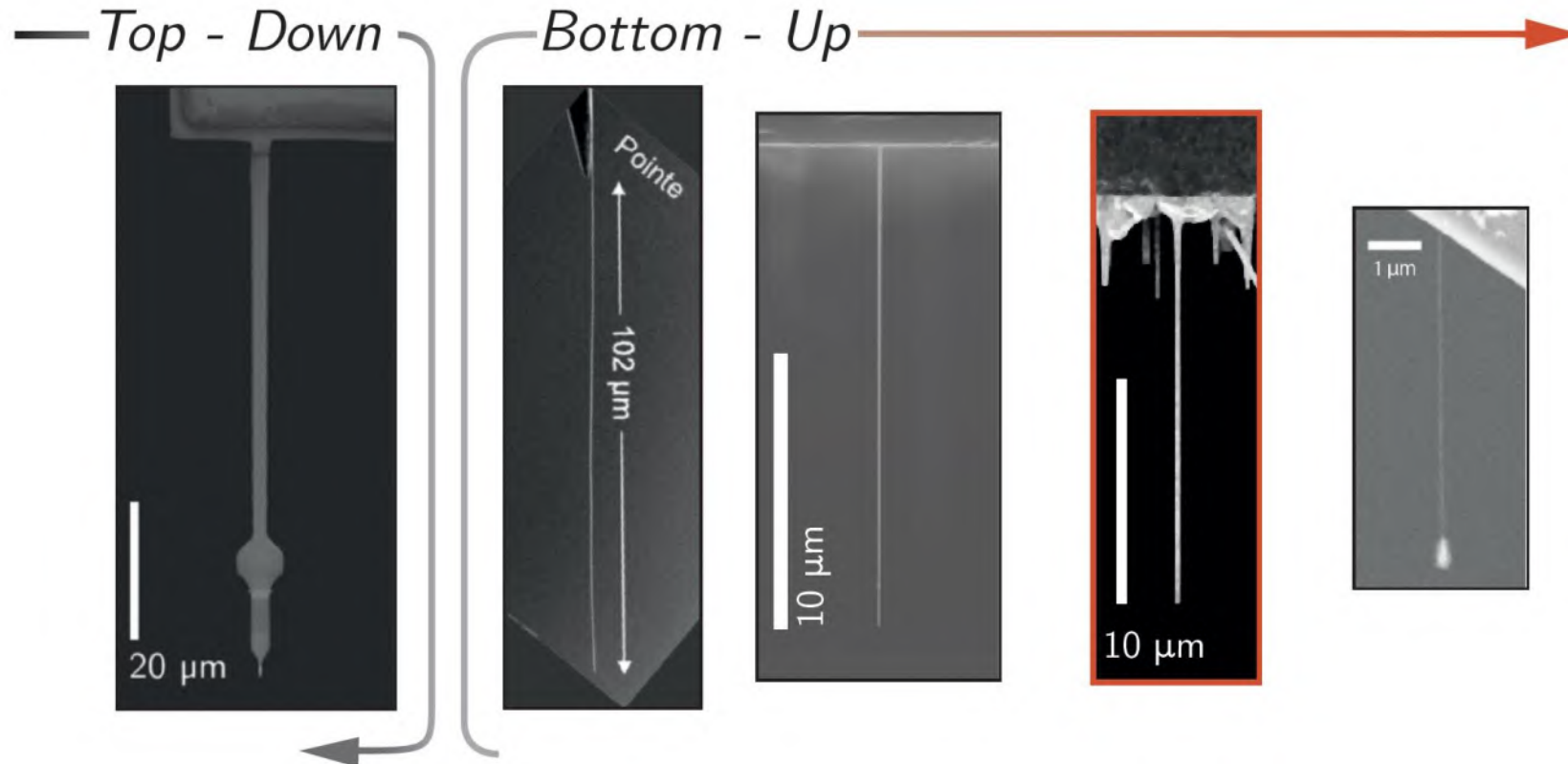
$$\Gamma \propto \frac{w t}{l}$$

Scale all lengths by  $\beta$ :

$$\Gamma \propto \beta \quad \omega_0 \propto \beta^{-1}$$

100 μm

# 'Bottom-up' scanning force sensors

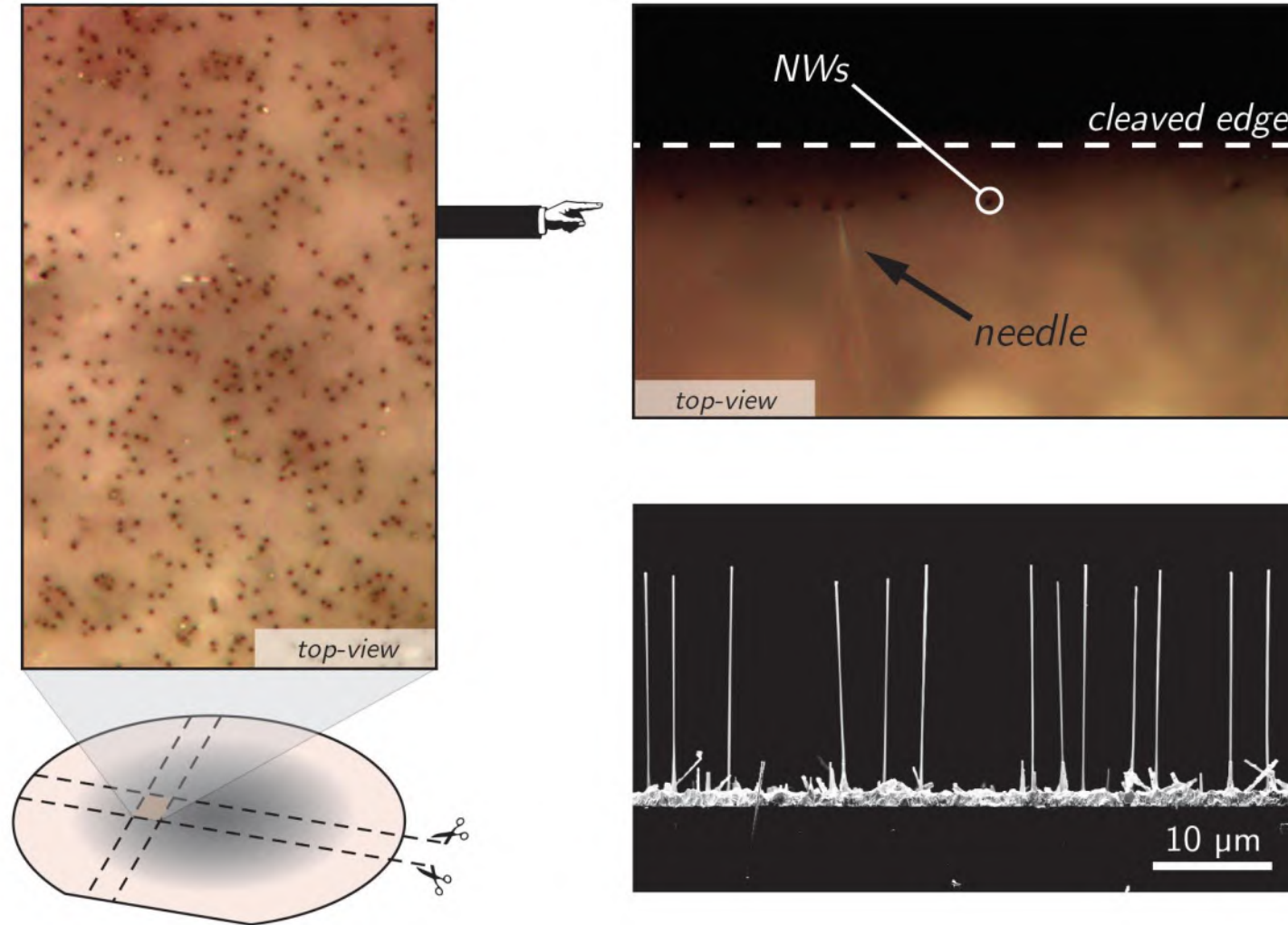


# NW Cantilevers

**Table 1.** Experimentally determined parameters of singly-clamped NW cantilevers. Here the diameter  $d$  is the average cross-sectional width and  $\omega_0/2\pi$  is the average frequency of the fundamental flexural mode doublet. The quality factor  $Q$  is the average value of the fundamental flexural mode doublet, taken for a freestanding NW, far from any sample surface and measured at low ambient pressures. RT stands for room temperature.

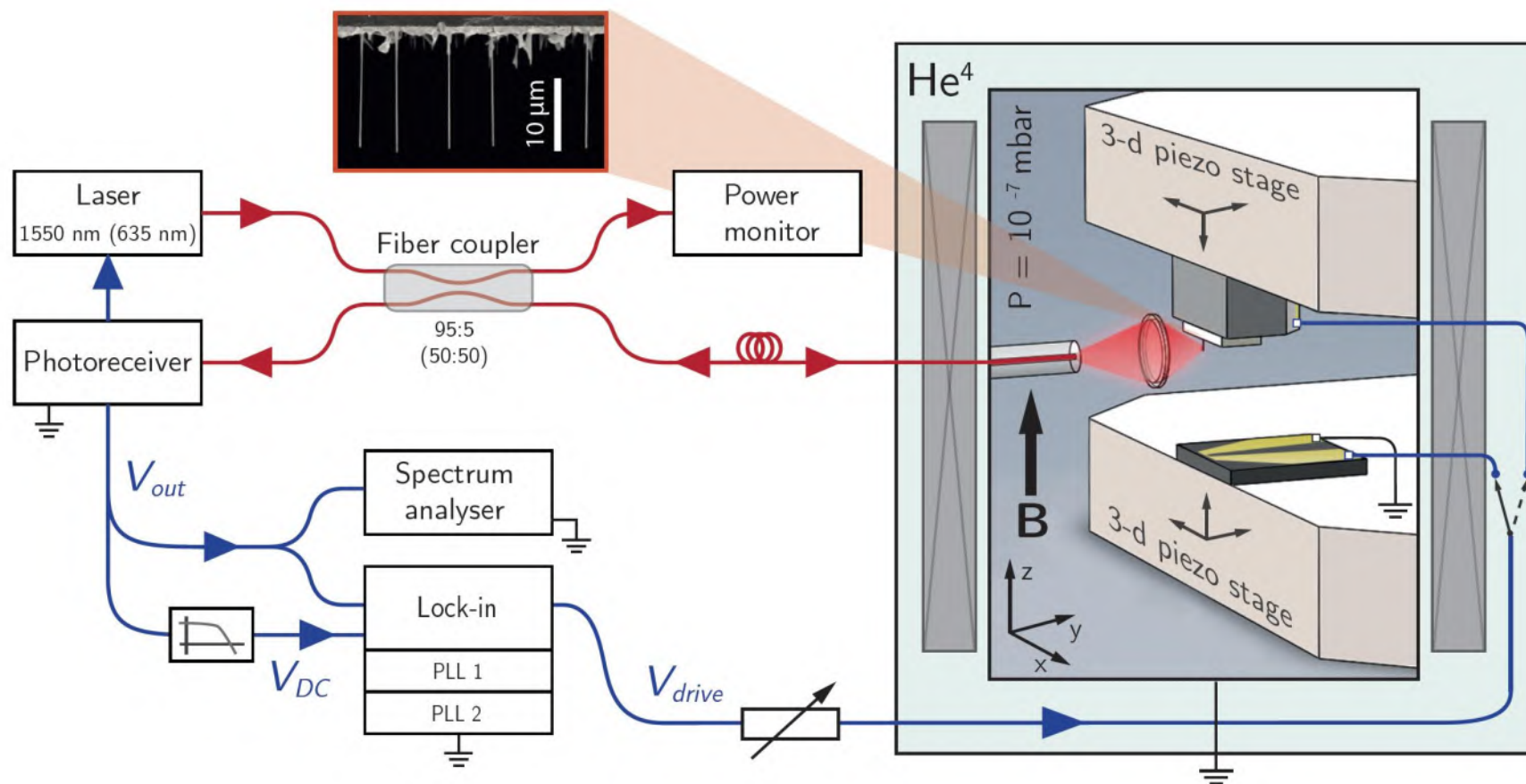
Material	Cross-section	$d$ (nm)	$L$ ( $\mu\text{m}$ )	$\omega_0/2\pi$ (kHz)	$k$ ( $\text{N m}^{-1}$ )	$Q$	Reference
GaAs/AlGaAs	Hexagonal	350	25	417	$1 \times 10^{-2}$	50 000 (4 K)	[9, 10]
GaAs	Hexagonal	234	16.8	598	$8.3 \times 10^{-3}$	46 553 (4 K)	[11]
GaAs	Hexagonal	100	<25	1197	$8.3 \times 10^{-3}$	4900 (RT)	[12]
GaAs/AlGaAs	Hexagonal	390	20	795	$9 \times 10^{-2}$	6700 (4K)	[13]
GaAs	Hexagonal	130	14.5	465	—	2000–3000 (RT)	[14]
InAs	Hexagonal	60–80	4–5.5	2023.9	$3.6 \times 10^{-3}$	1752 (RT)	[15]
SiC	Circular	150	52	113	$4 \times 10^{-4}$	2890 (RT)	[1]
SiC	Circular	200	50	78	$1.5 \times 10^{-4}$	1000 (RT)	[16]
SiC	Circular	120	165	6.7	$3 \times 10^{-6}$	3000 (RT)	[17]
SiC	Circular	284	128	33	—	36 000 (RT)	[18]
SiC	Circular	206	93	43	—	159 000 (RT)	[18]
SiC	Circular	50	7	1519	—	2500 (RT)	[19]
SiC	Circular	300	6	6140	1.5	33 (RT, Air)	[20]
Si	Circular	44	14.4	210.5	$2.8 \times 10^{-5}$	9250 (RT)	[21]
Si	Circular	46	12.9	273	$6.6 \times 10^{-5}$	7250 (RT)	[21]
Si	—	35	15	1060	$6.5 \times 10^{-4}$	25 000 (8 K)	[6]
Si	—	50	15	333	$1.5 \times 10^{-4}$	18 000 (6 K)	[7]
Si	Circular	50	15	197.5	$2.0 \times 10^{-5}$	3000–3500 (RT)	[22]
Si	Elongated circular	60, 80	20	342	$1 \times 10^{-4}$	8150 (4K)	[8]
Si	Hexagonal	100–300	5–10	2000–6000	—	2000 (RT)	[23]
Si	Hexagonal	165	12.7	1772.4	—	3000 (RT)	[24]
Si	Hexagonal	90	9.3	2504.3	—	3000 (RT)	[24]
Si	Hexagonal	100–200	6–8	3500–4000	$2.4 - 5 \times 10^{-2}$	3000–3500 (RT)	[25]
Si	Hexagonal	150 (clamp), 60 (tip)	11.3	2480	—	—	[26]
Si	Hexagonal	39–400	2–20	1000–12 000	—	3000–25 000 (RT)	[27]
Si (metallized)	Hexagonal	142	2.25	200 000	110.3	2000 (25 K)	[28]
Si (metallized )	Hexagonal	118	2.1	188 000	62.9	2500 (25 K)	[28]
Si	Hexagonal	81	1.69	215 000	31.4	5750 (25 K)	[28]
Si	Hexagonal	74	2.77	80 000	6.0	13 100 (25 K)	[28]
CNT	Circular	50	18	270	$\sim 10^{-4}$	250 (RT)	[29]
CNT	Circular	1–3	5	38 178.5	$4.5 \times 10^{-8}$	2245 (RT)	[30]
CNT	Circular	4	1.2	5955	$2.1 \times 10^{-5}$	—	[31]
CNT	Circular	—	—	363.5	$4.8 \times 10^{-6}$	571 (RT)	[31]

# GaAs NWs

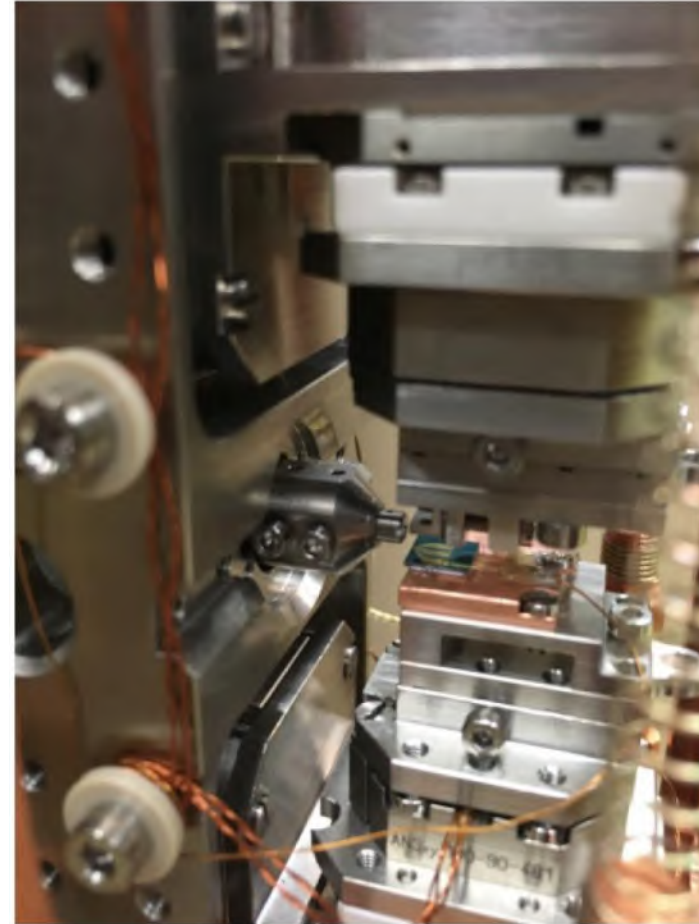


NWs from Fontcuberta group.

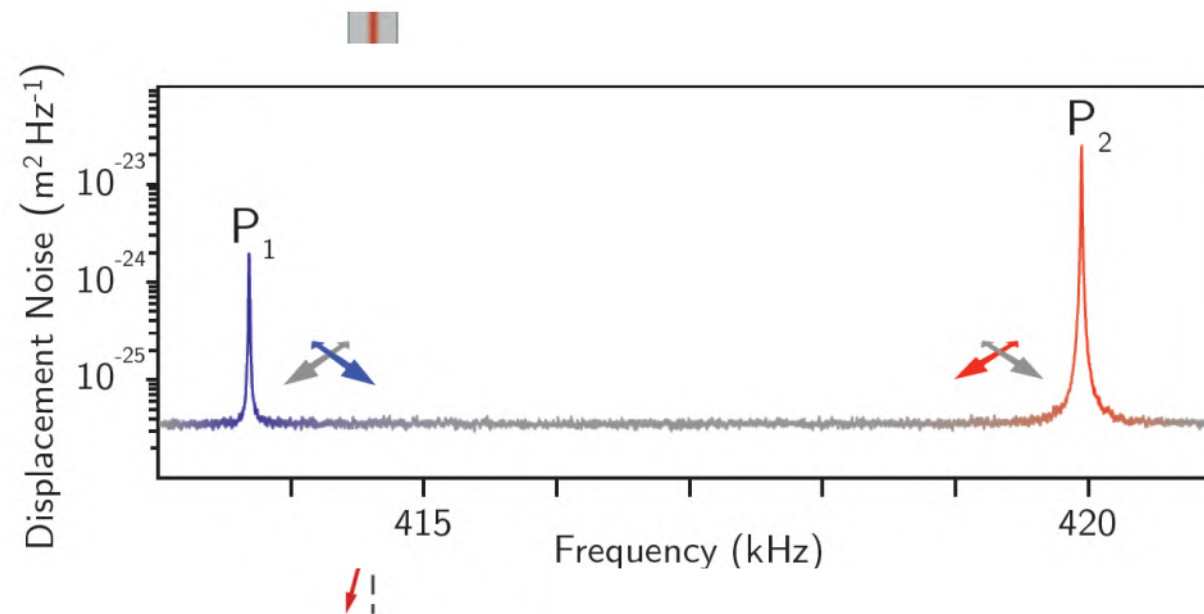
# NW force microscope



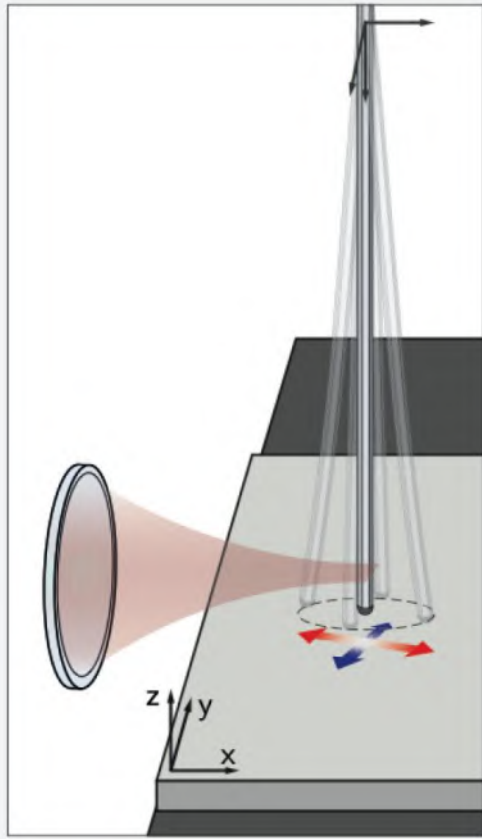
# NW force microscope



# Interferometric displacement detection



# Scanning nanowire microscopy



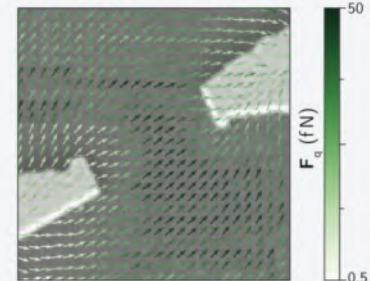
## Electrostatic force

- $\mathbf{F}_q = q\mathbf{E}$
- $V_{drive}$  sweep through  $f_{1,2}$
- $q_{tot} = 30 \pm 10e$

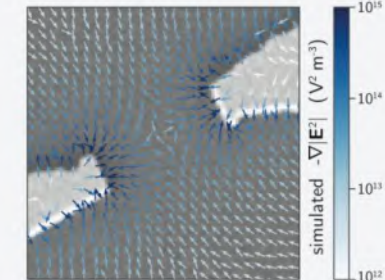
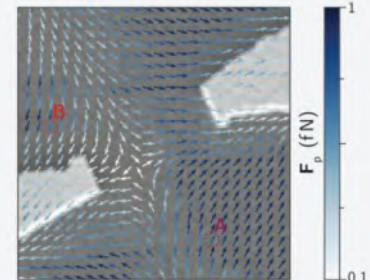
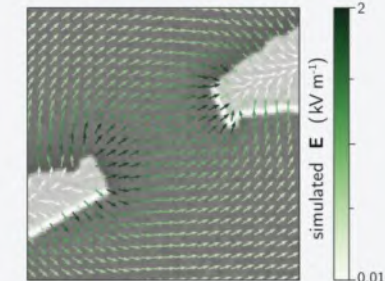
## Dielectric force

- $\mathbf{F}_p = -\nabla(\alpha|\mathbf{E}|^2)$
- $V_{drive}$  sweep through  $\frac{f_{1,2}}{2}$
- $\alpha = 10^{-29} \frac{C}{Vm}$

## Experiment



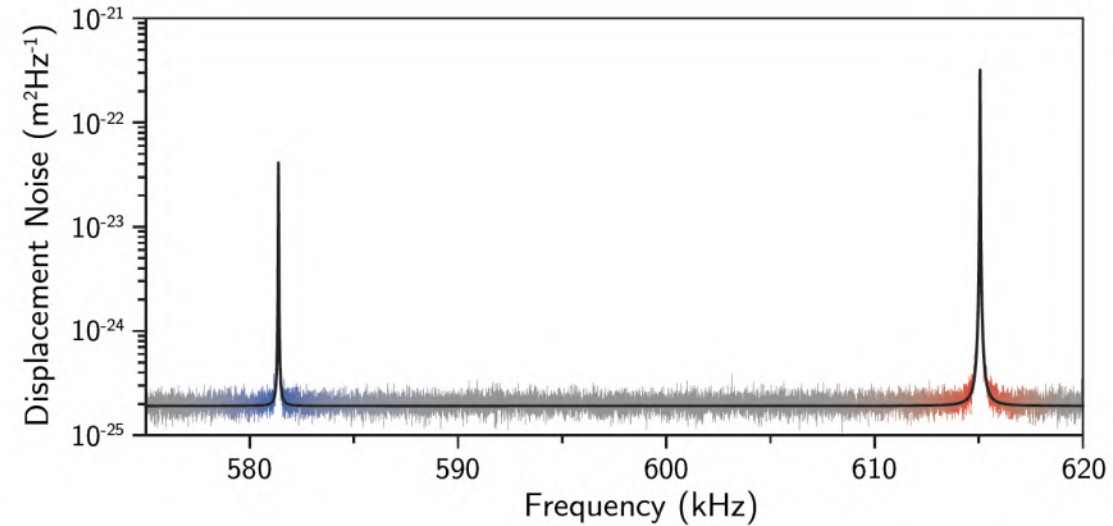
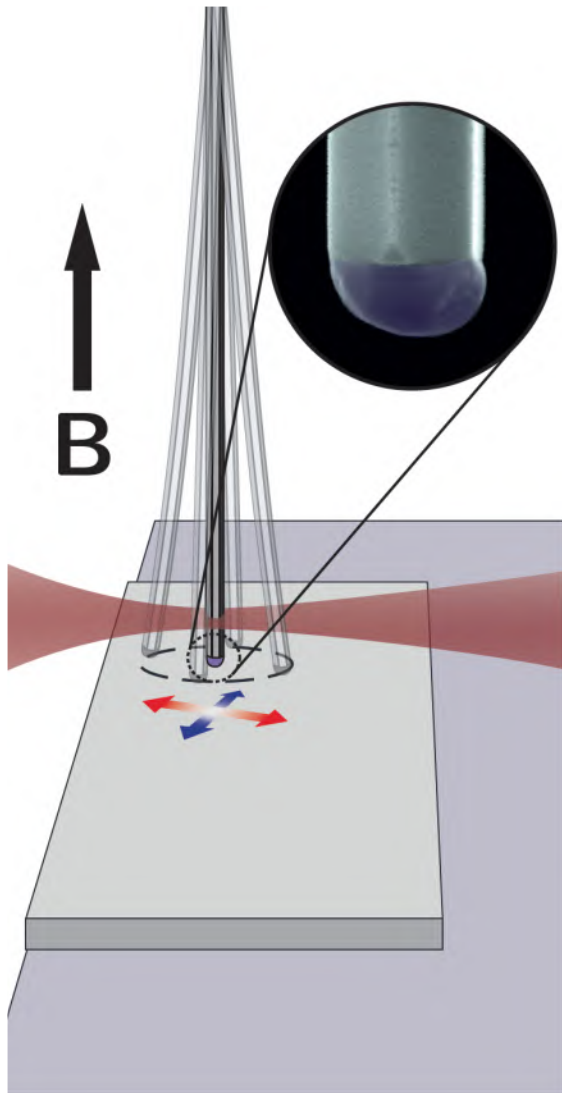
## Simulation



Rossi et al., *Nat. Nanotechnol.* **12**, 150 (2017).

Mercier de Lépinay et al., *Nat. Nanotechnol.* **12**, 156 (2017).

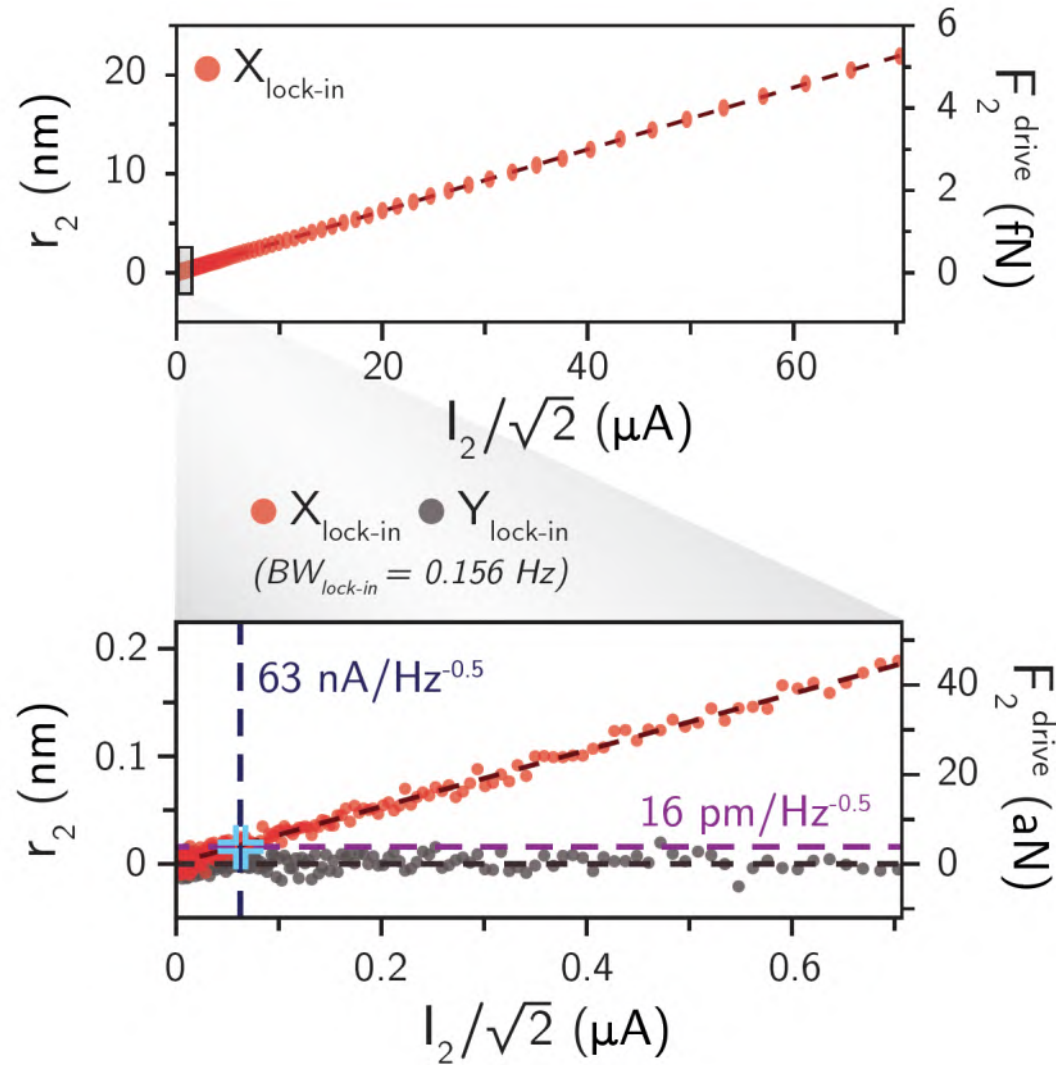
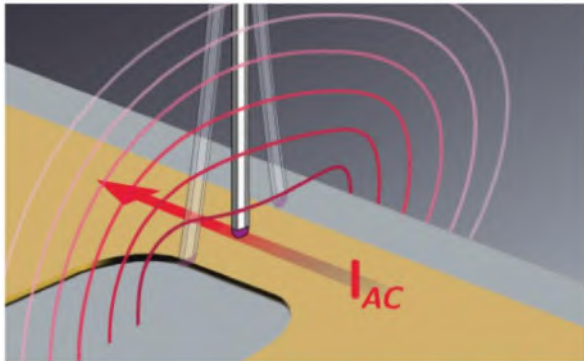
# NWs with magnetic tips



Length  $\sim 17 \pm 1 \mu\text{m}$  with diameter  $\sim 225 \pm 15 \text{ nm}$

- $f \sim [500 - 700] \text{ kHz}$
- $Q \sim [30 - 50] \times 10^3$
- $k \sim [1 - 10] \text{ mN/m}$
- $M \sim 700 \text{ fg}$
- $\Gamma \sim 50 \times 10^{-15} \text{ kg/s}$
- $F_{min} \sim 4 \text{ aN}/\sqrt{\text{Hz}}$

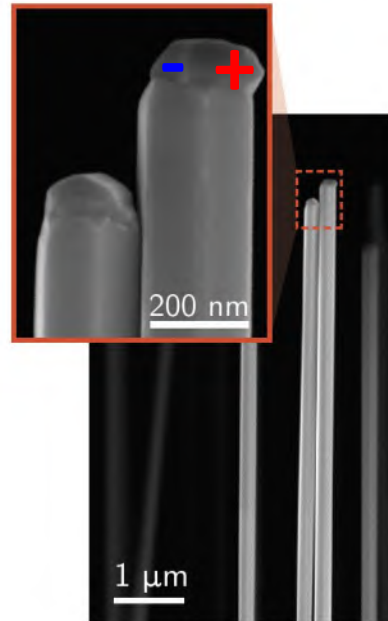
# Quantifying sensitivity



Rossi et al., *Nano Lett.* **19**, 930 (2019).

# Quantifying sensitivity

MBE-grown MnAs-tipped NWs



$$F_{\min} = 4 \text{ aN}/(\text{Hz})^{1/2}$$

At 250 nm spacing:

$$dB/dx_{\min} = 11 \text{ mT}/\text{m}(\text{Hz})^{1/2}$$

FEBID-grown Co NWs



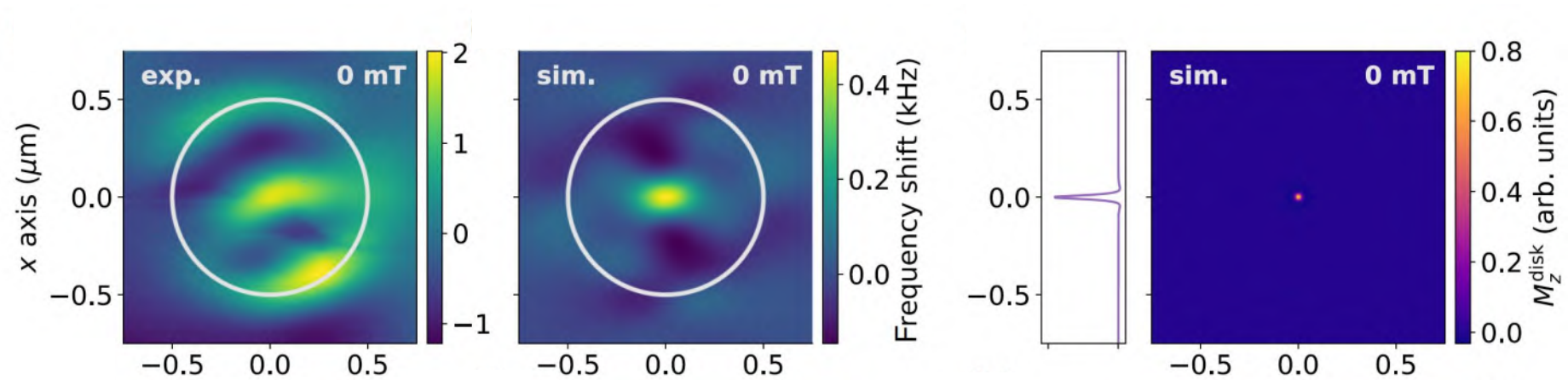
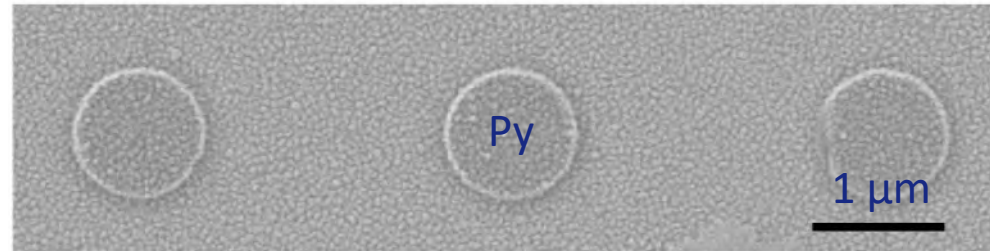
$$F_{\min} = 25 \text{ aN}/(\text{Hz})^{1/2}$$

At 200 nm spacing:

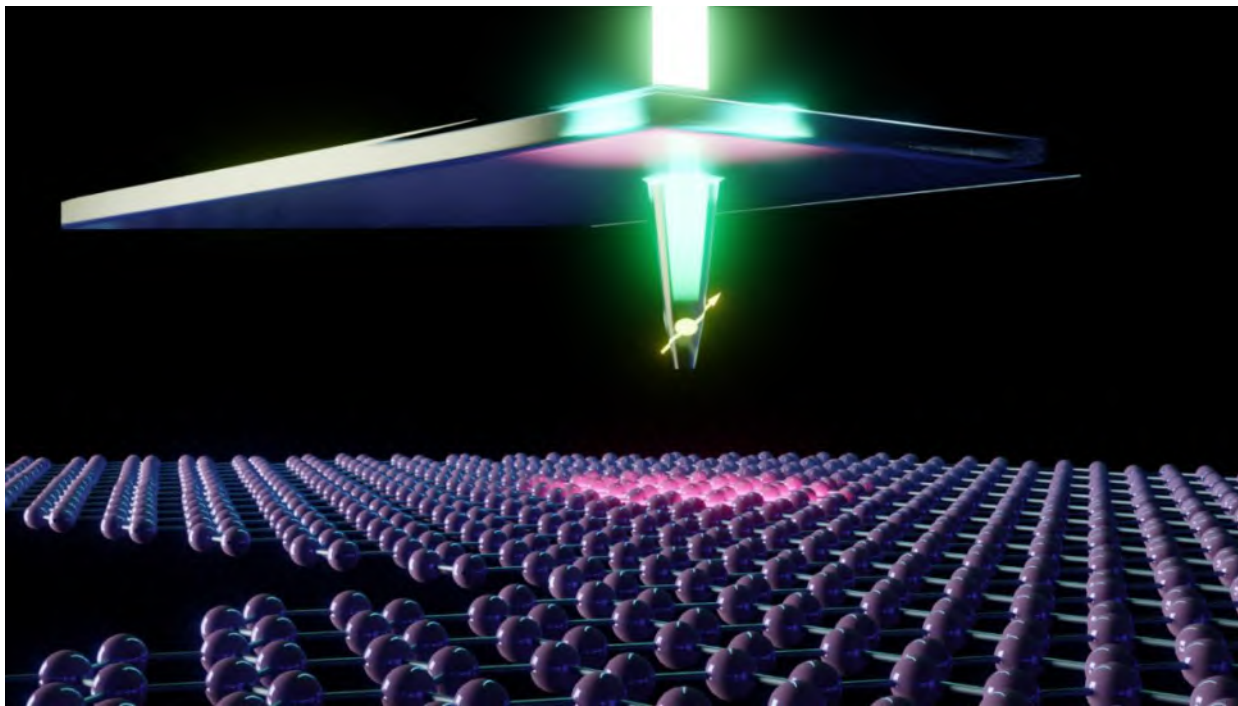
$$B_{\min} = 3 \text{ nT}/(\text{Hz})^{1/2}$$

Rossi et al., *Nano Lett.* **19**, 930 (2019).  
Mattiati et al., *Phys. Rev. Appl.* **13**, 044043 (2020).

# NW MFM



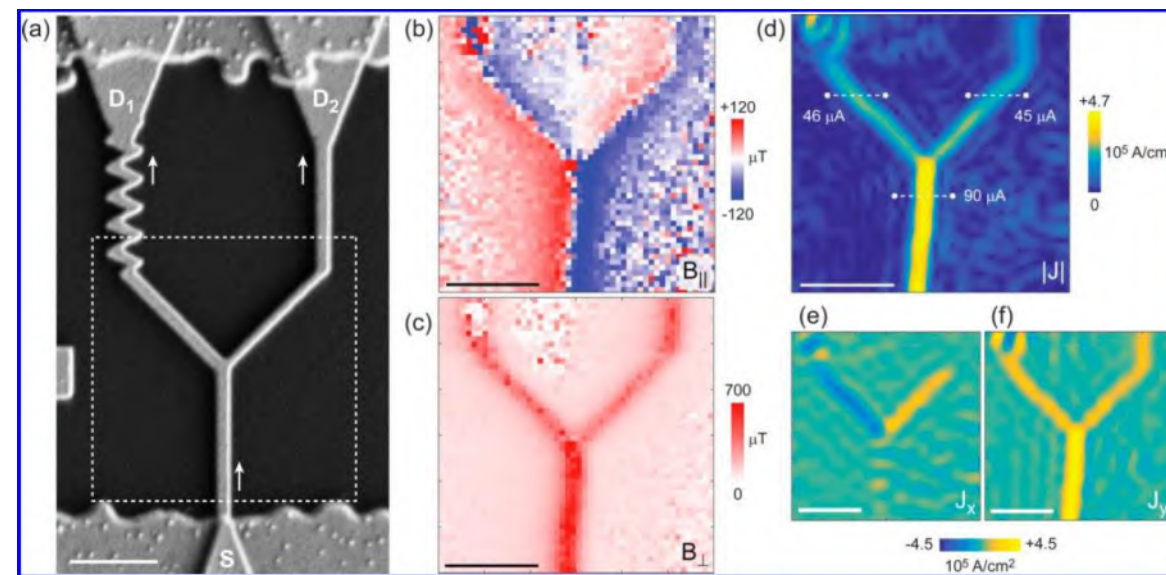
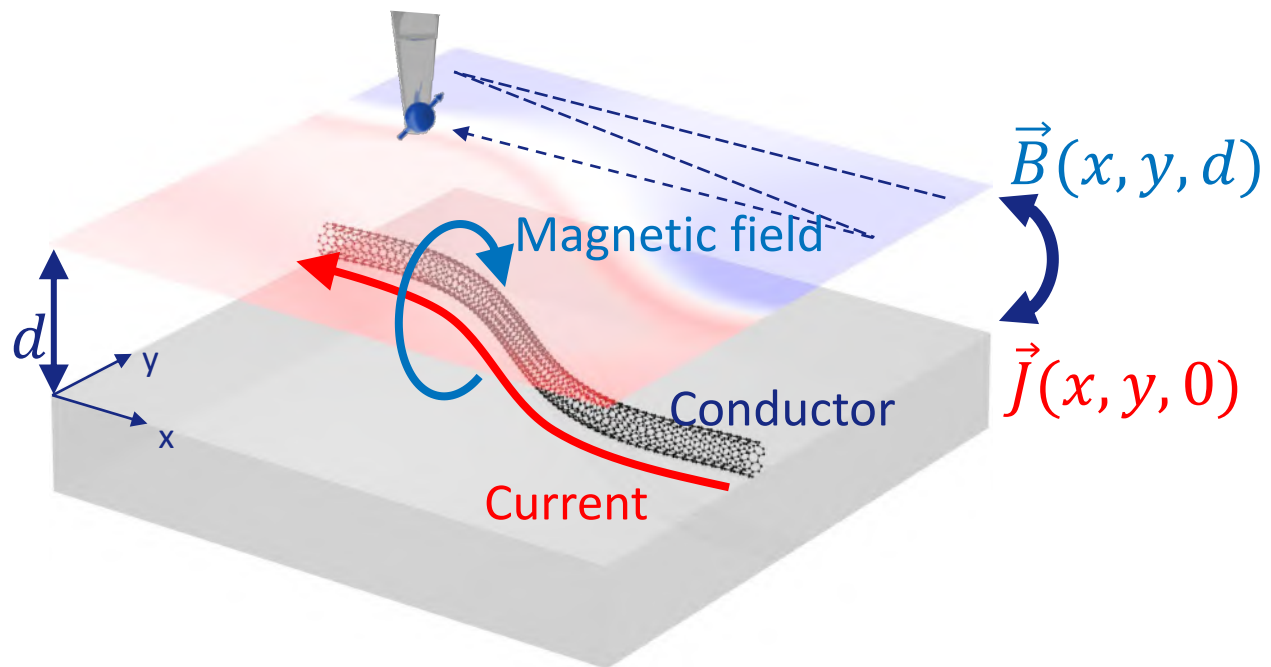
# Scanning Nitrogen-vacancy Center Microscopy (SNVM)



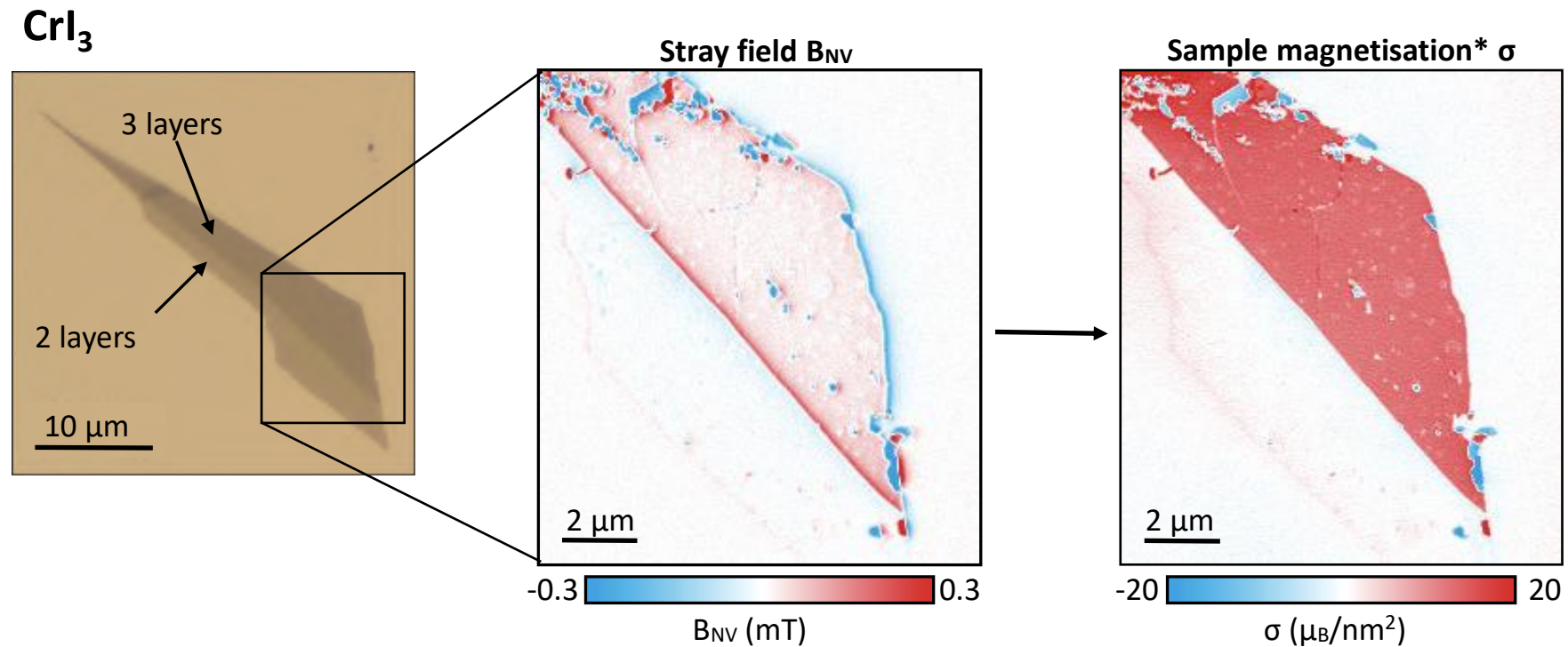
Sensitivity down to  
 $100 \text{ nT}/(\text{Hz})^{1/2}$

Spatial resolution  
down to 10 nm

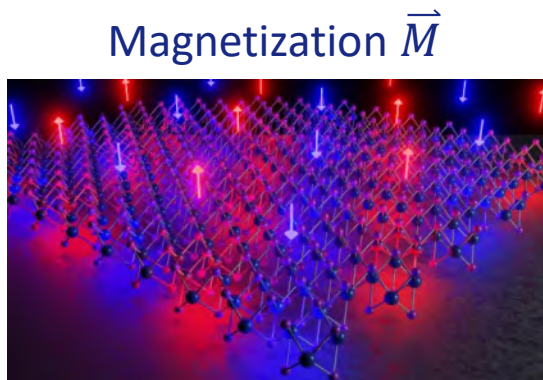
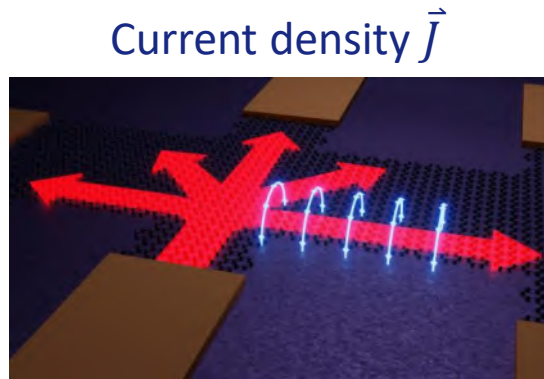
# Imaging current with SNVM



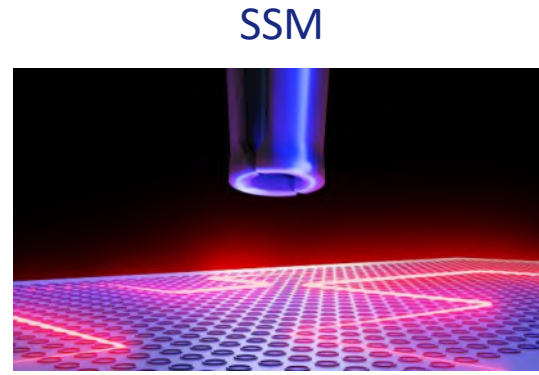
# Scanning NV microscopy of 2D magnets



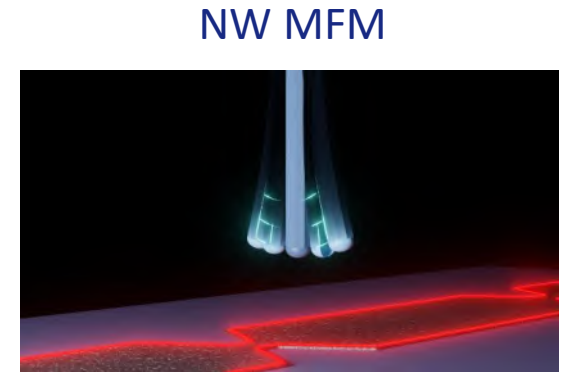
# Contrast & Techniques



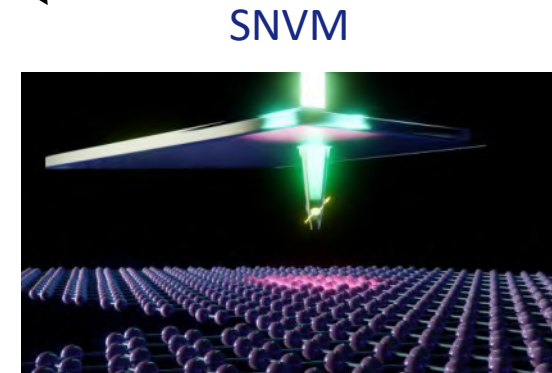
Magnetic field  $\vec{B}$



Magnetic flux  $\Phi_z$

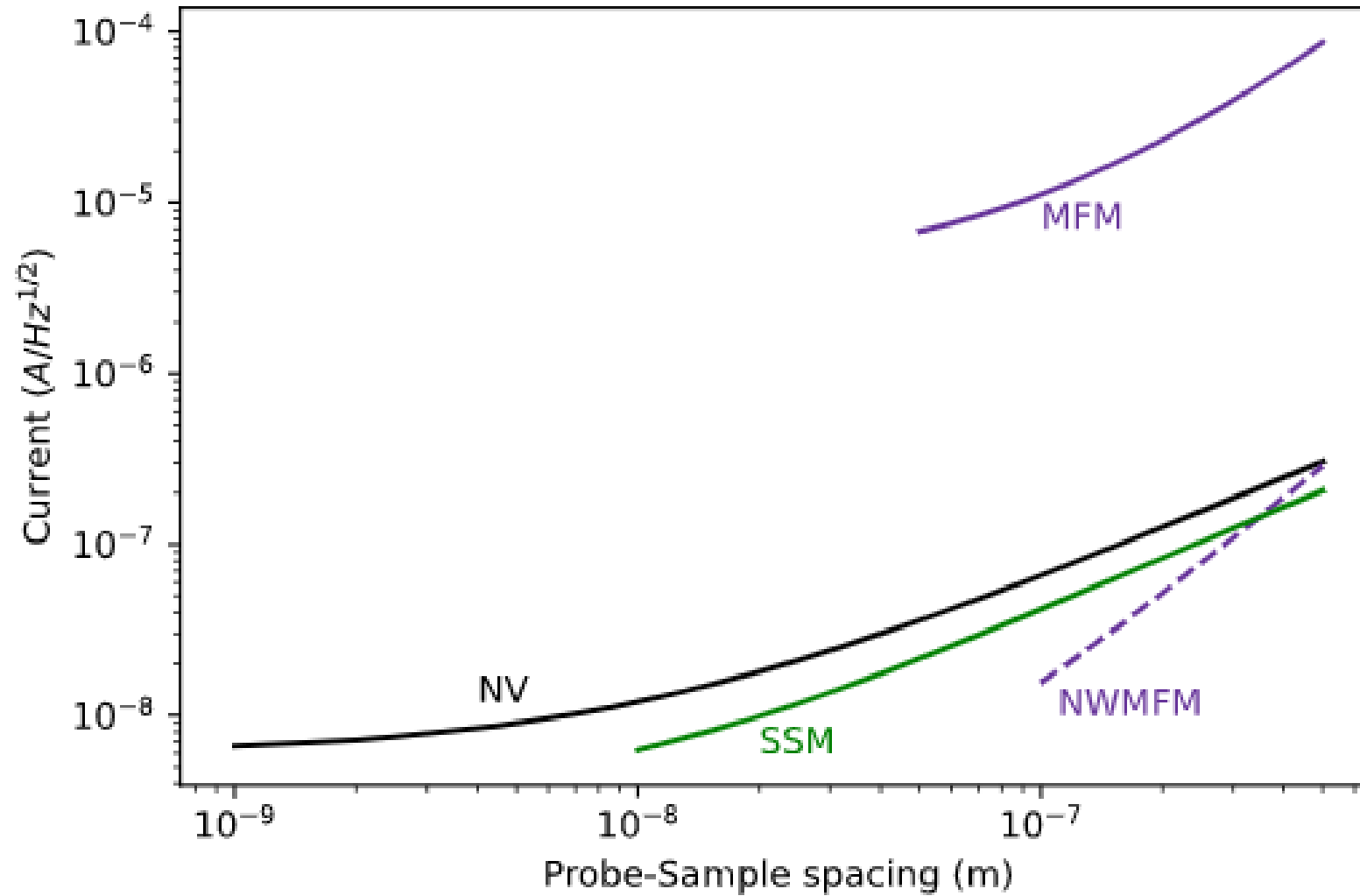


Magnetic field derivative  $\frac{\partial B_z}{\partial x}$

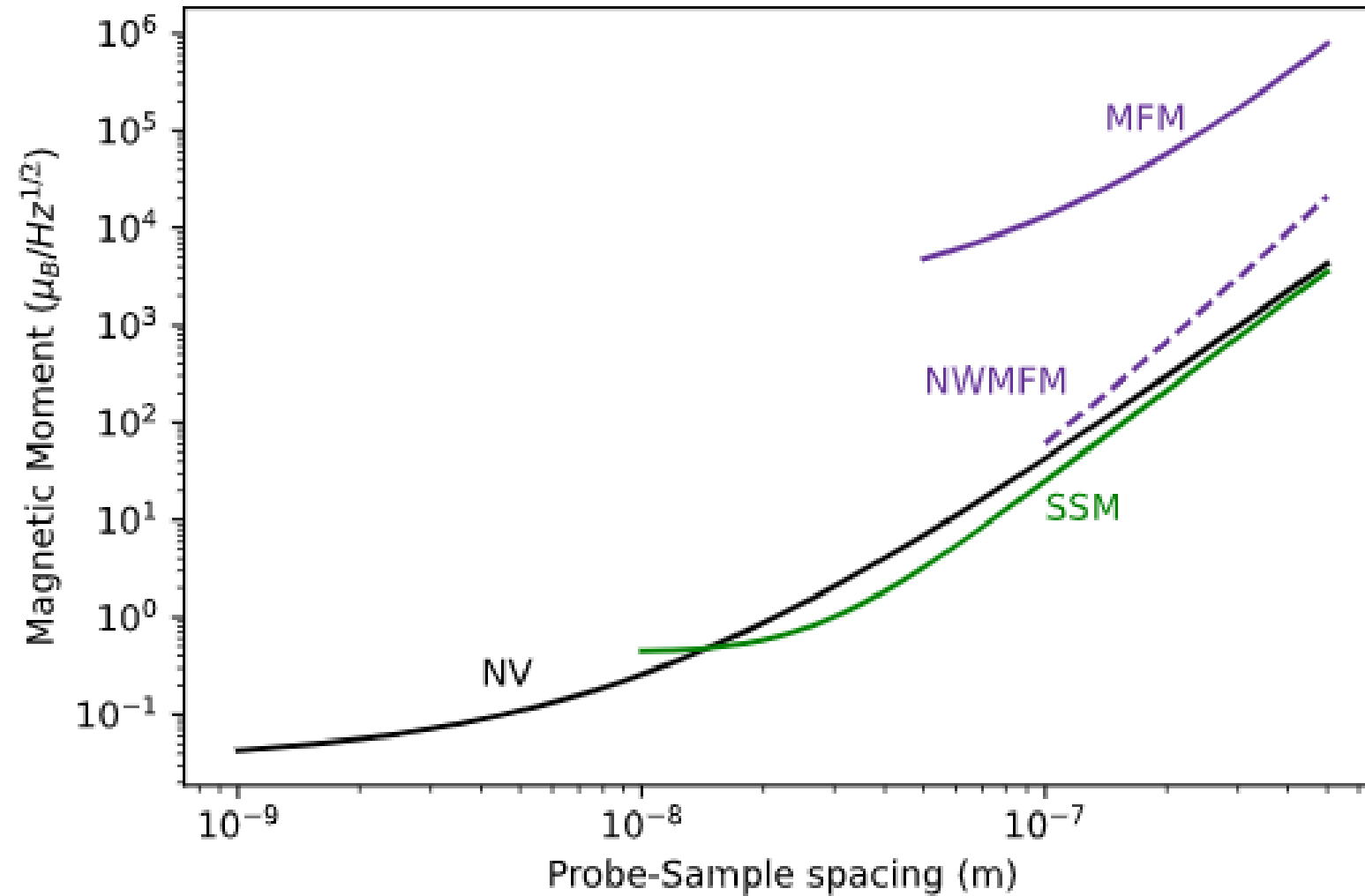


Magnetic field component  $B_z$

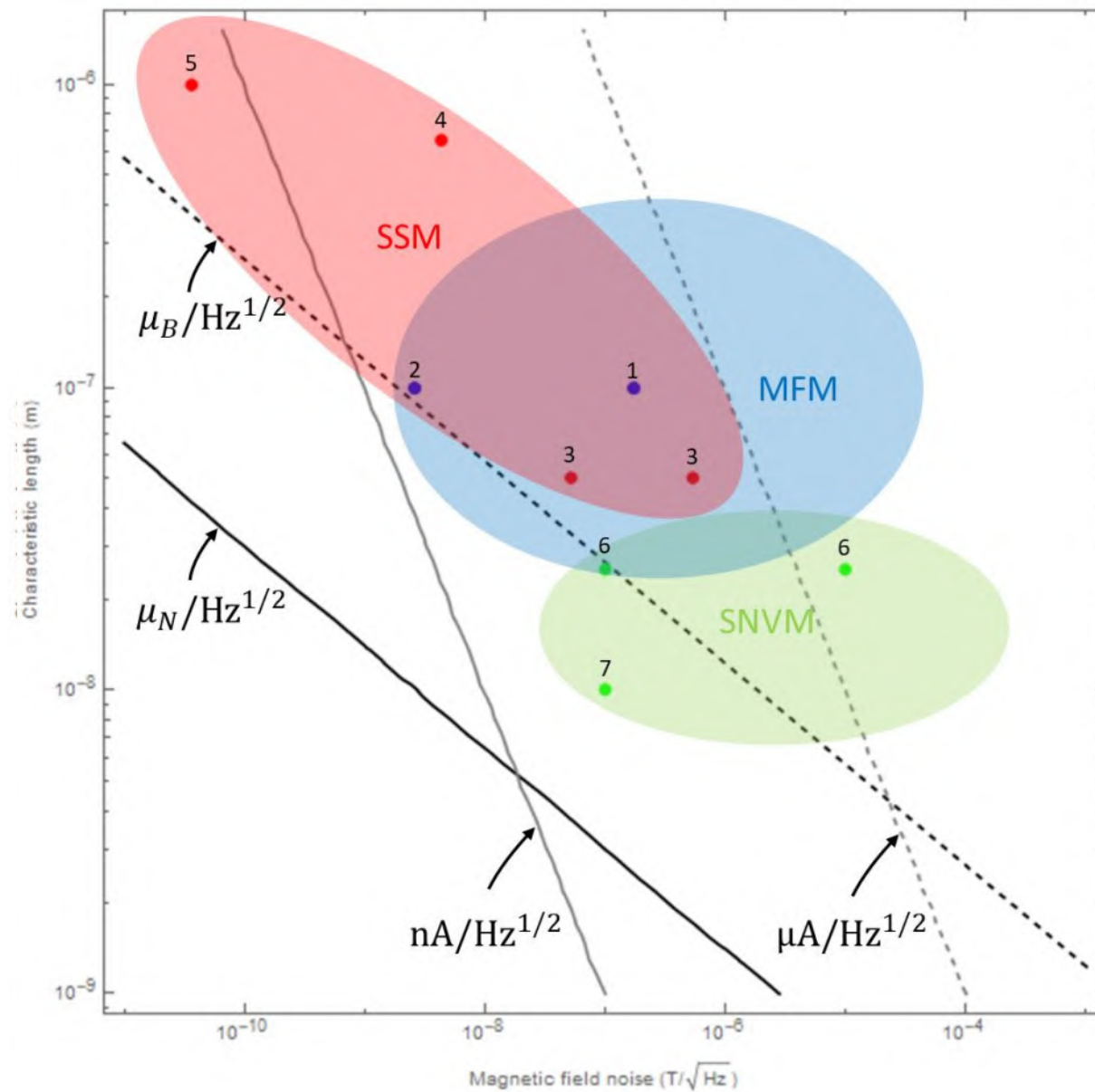
# Sensitivity to Current



# Sensitivity to Magnetization

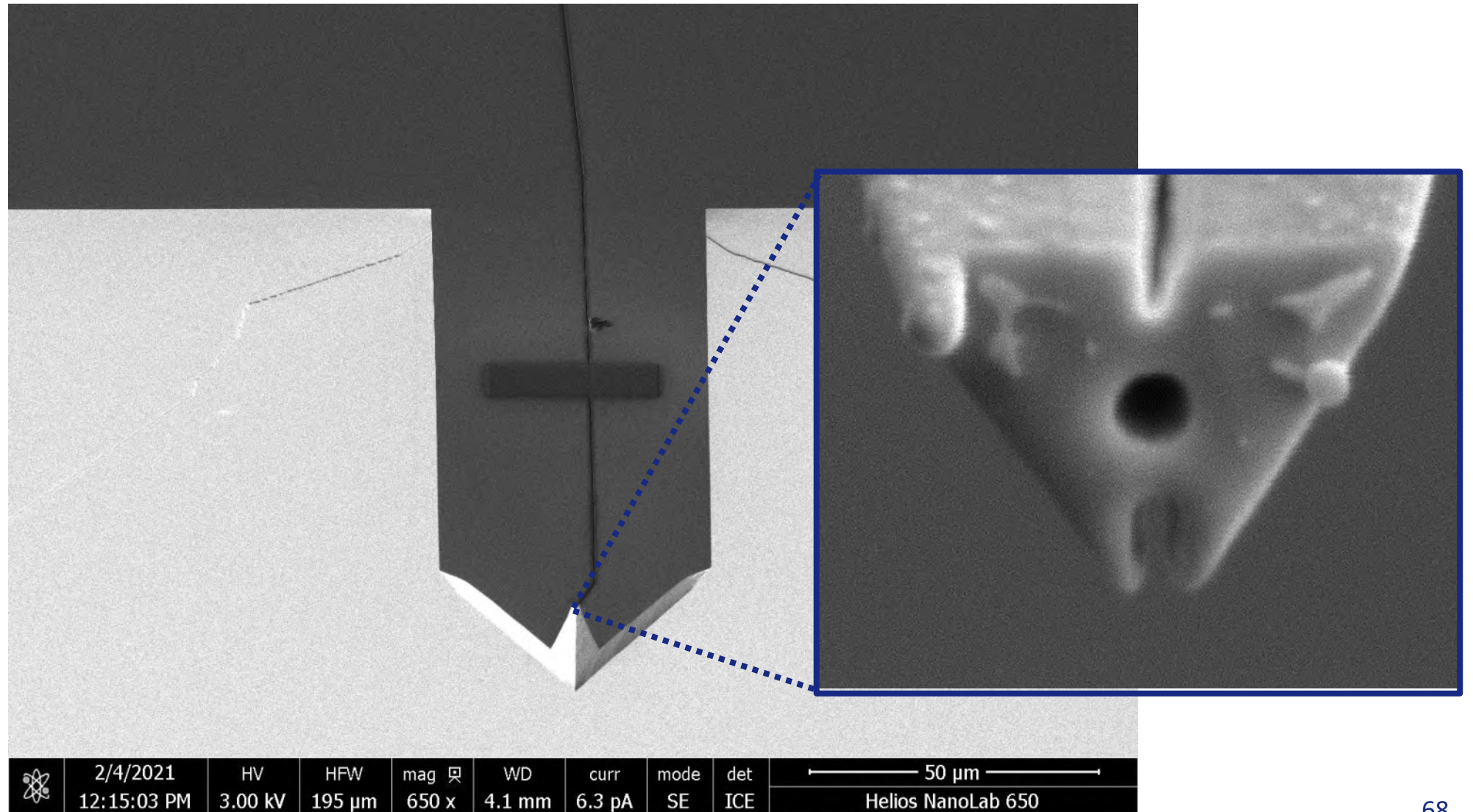


# State of the Art

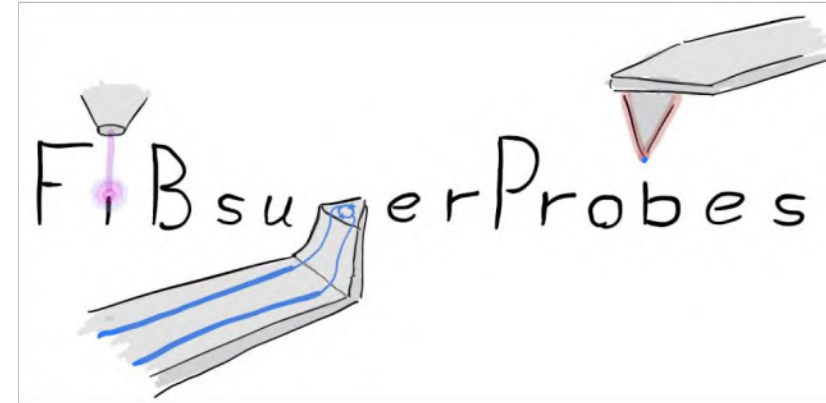


# SQUID-on-lever (SOL)

Machining cantilevers by Focused Ion Beam (FIB)



# Focused Ion Beam fabrication of superconducting scanning Probes (FIBsuperProbes)



- 2020 - 2024
  - Basel (Coordinator)
  - CSIC Zaragoza
  - Tübingen
  - IBM Zürich

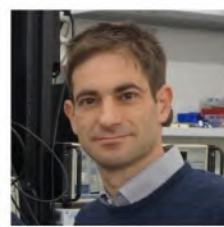


# POGGIO LAB

poggiolab.unibas.ch



## Funding:



Prof. Martino Poggio  
Principal Investigator



Dr. Floris Braakman  
Research Scientist



Dr. Boris Groß  
Research Scientist



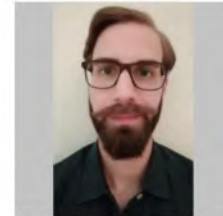
Dr. Marcus Wyss  
Post-doctoral Researcher



Dr. Estefani Marchiori  
Post-doctoral Researcher



Dr. Lorenzo Ceccarelli  
Post-doctoral Researcher



Dr. Francesco Fogliano  
Post-doctoral Researcher



Dr. Kousik Bagani  
Post-doctoral Researcher



Thibaud Ruelle  
Ph.D. Student



Simon Philipp  
Ph.D. Student



Giulio Romagnoli  
Ph.D. Student



David Jaeger  
Ph.D. Student



Hinrich Mattiat  
Ph.D. Student



Lukas Schneider  
Ph.D. Student



Andriani Vervelaki  
Ph.D. Student



Daniel Jetter  
Ph.D. Student



Mathias Claus  
Masters Student

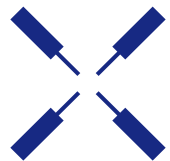


Aurèle Kamber  
Masters Student

# Zurich Instruments

## Company profile

- Headquarters in Zurich, Switzerland
- Founded in 2008, 90+ people, 20+ nations
- Offices in China, USA, Italy, Korea, France
- Partners in Japan, Taiwan, Australia
- Run by scientists for scientists



Zurich  
Instruments



Q&A

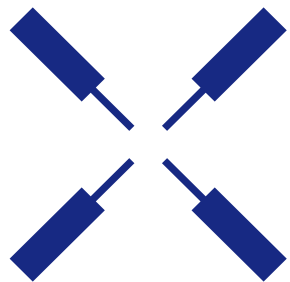
Thank you!



Prof. Martino Poggio  
[martino.poggio@unibas.ch](mailto:martino.poggio@unibas.ch)



Dr. Jelena Trbovic  
[jelena.trbovic@zhinst.com](mailto:jelena.trbovic@zhinst.com)



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